



PSD10: 10th International Conference on Position Sensitive Detectors
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Charge Collection Efficiency of micro-strip Silicon Sensors designed for studying Charge Multiplication after Hadron irradiation

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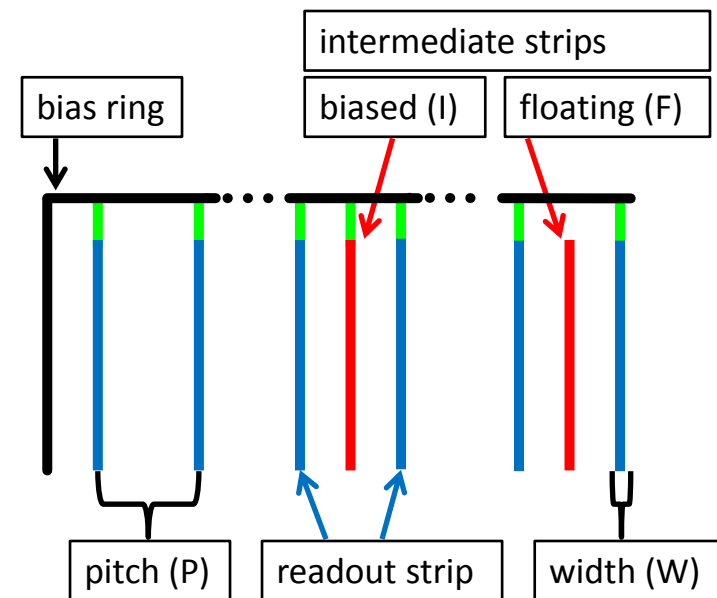


- Charge Multiplication Sensors
- ALiBaVa readout system
- Charge Collection measurement results
- Long term room temperature annealing
- TCT/eTCT system and results



- At high fluences and bias voltages, charge multiplication of the signal in the detector has been observed
- Multiplication due to impact ionisation
 - Begins when electric field reaches 10-15 V/ μm
- Charge multiplication can be beneficial for sensors, leading to higher signal
 - Particular for not fully depleted sensors after high irradiation doses
- Same process that is responsible for charge multiplication also leads to increased noise and lower breakdown voltage

- Dedicated charge multiplication sensors, produced by Micron Semiconductor Ltd (UK)
 - Detectors aim to enhance the electric field near the readout strips
- 1cm x 1cm, n-in-p FZ strip detectors
- Various strip pitch (P) and width (W)
- Some sensors with floating (F) or biased (I) intermediate strips between readout strips



Serial No	Thickness [μm]	Resistivity [$\text{k}\Omega/\text{cm}$]	Implant Details	Labelling
2912-(2,3)	300	10-13	Standard, double implant energy	2E imp
2935-10	305	13	Standard, double diffusion time	extra diff
2935-(2,4,5,6,7,8,9)	305	13	Standard	std
2488-(6,7)	675*	8	Thick	thick
2885-5	150	10	Thin	thin

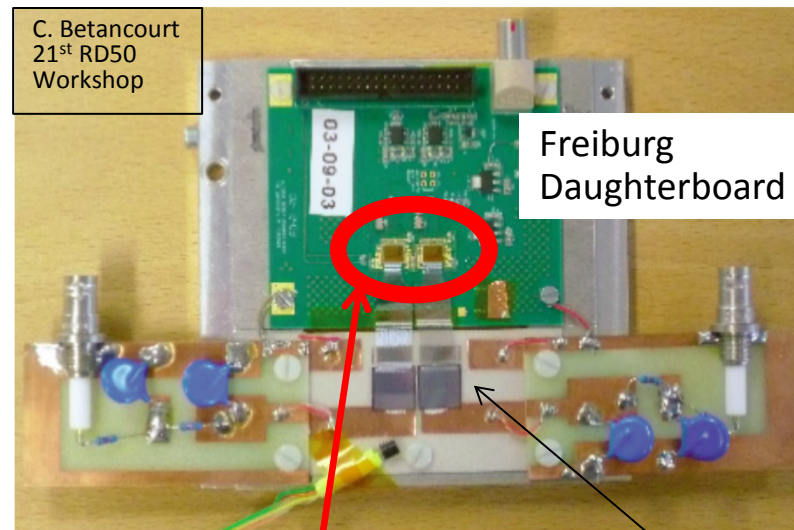
*: sensors should be 675 μm thick, but are only 300 μm thick



Use ALiBaVa system for charge collection measurements

- Up to 2 sensors are attached to Beetle chips (ASIC) on the daughterboard for analogue readout (signal amplification and shaping)
- High voltage connection to bias ring on daughterboard
- Daughterboard connected to motherboard, controlled by an FPGA (signal conversion into digital counts using a 10-bit Analogue to Digital Converter)
- Raw data sent to PC via USB cable and analysed by custom software based off the ROOT framework

C. Betancourt
21st RD50
Workshop

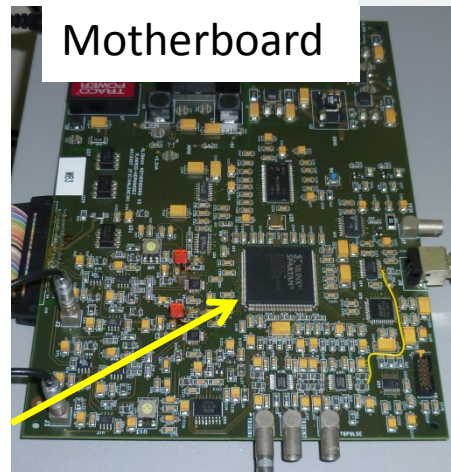


Freiburg
Daughterboard

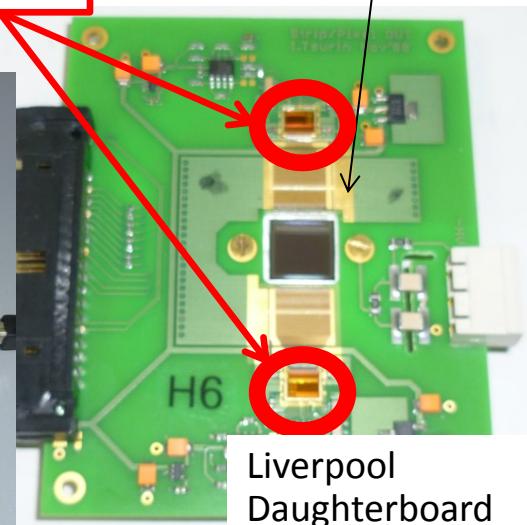
Beetle
Chip

Sensor

Motherboard



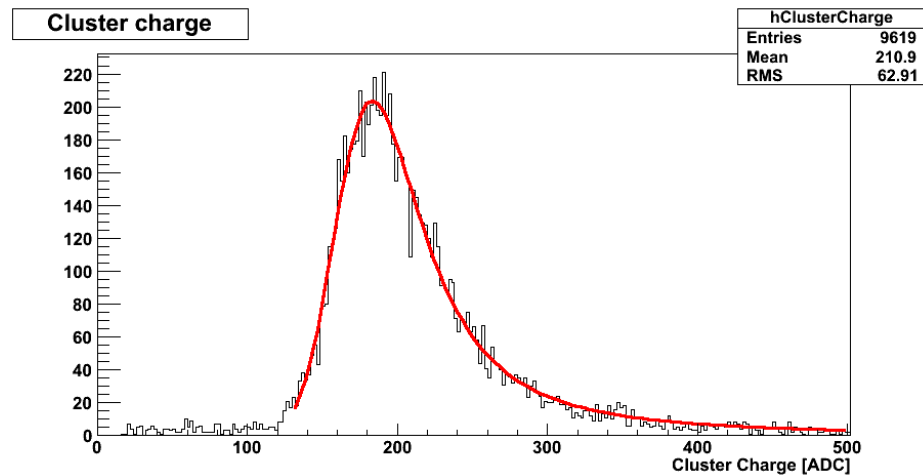
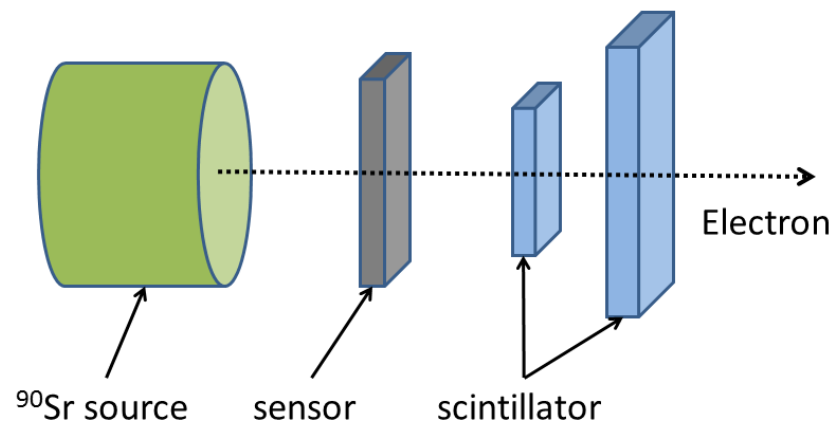
FPGA



Liverpool
Daughterboard



- MIP's from ^{90}Sr source to perform charge collection measurements
- Scintillators for triggering
- Resulting spectrum is fitted with a convolution of a Gaussian and Landau distribution to determine MPV
- With calibration value of daughterboard the collected charge is calculated from the MPV
- Irradiated sensors measured at temperatures between -20°C and -30°C in a freezer



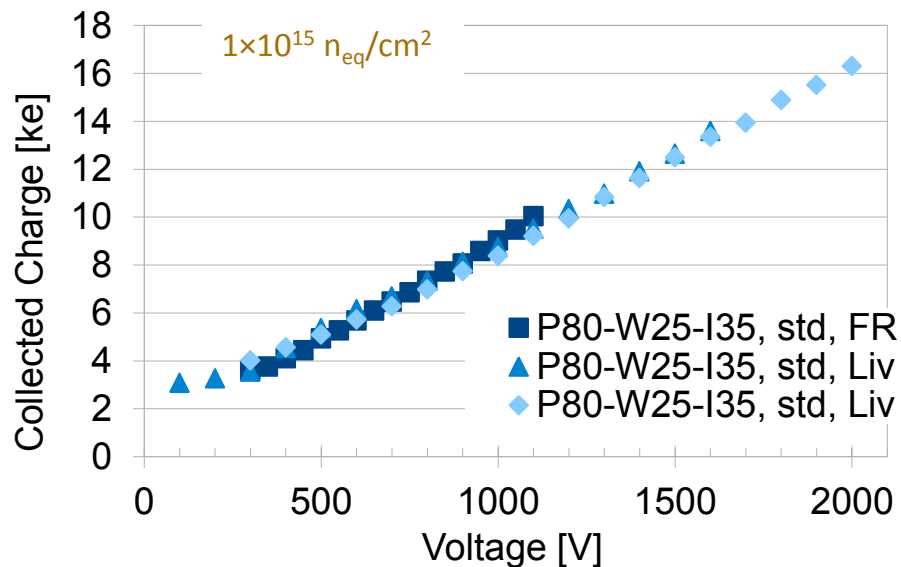
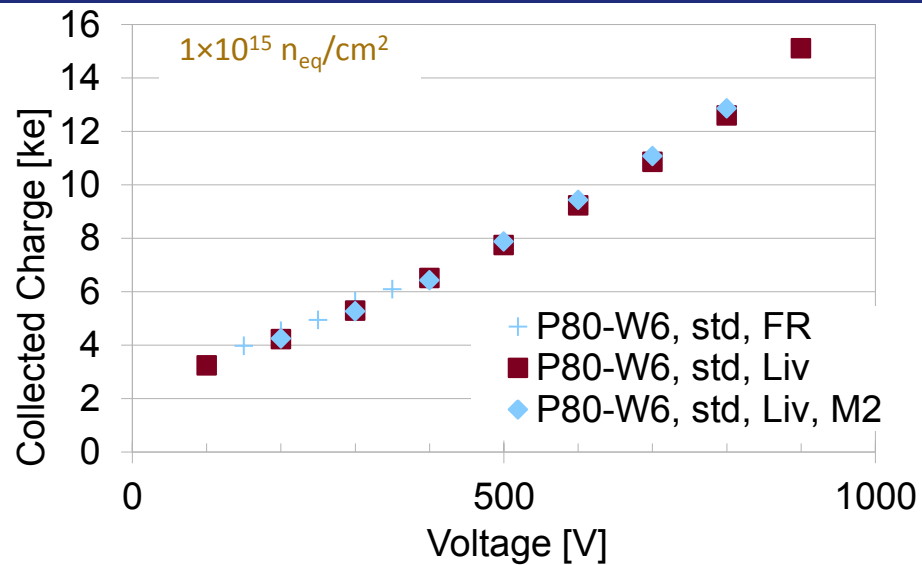
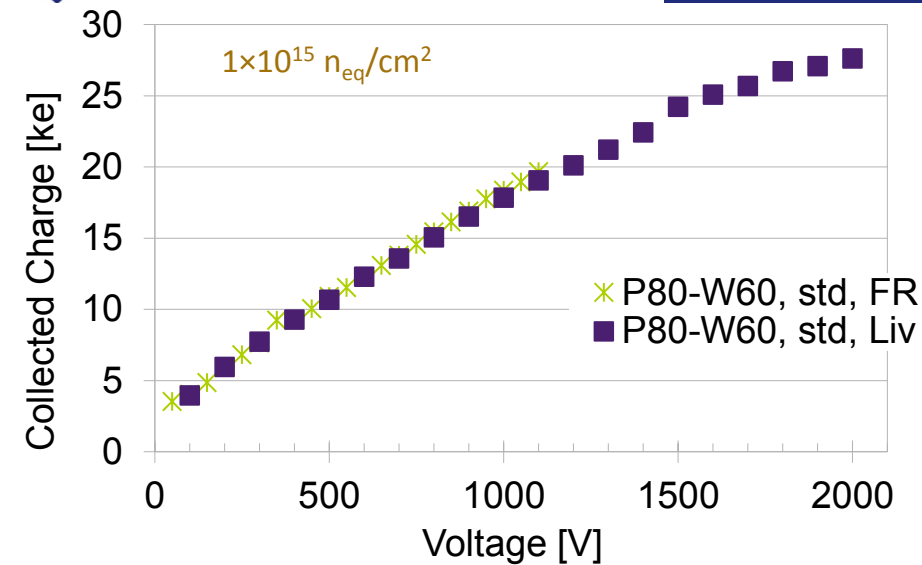


The sensors were irradiated with protons and neutrons to two fluences:

- Proton irradiation performed at Proton-Compact-Cyclotron at Karlsruhe (D) with 25MeV protons
 - Fluence of $1 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
 - Only measured at Freiburg
- Neutron irradiation at Jozef Stefan Institute in Ljubljana (SI) with reactor neutrons from TRIGA Mark II research reactor
 - Fluences of $1 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$ and $5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
 - Measured at Freiburg and Liverpool



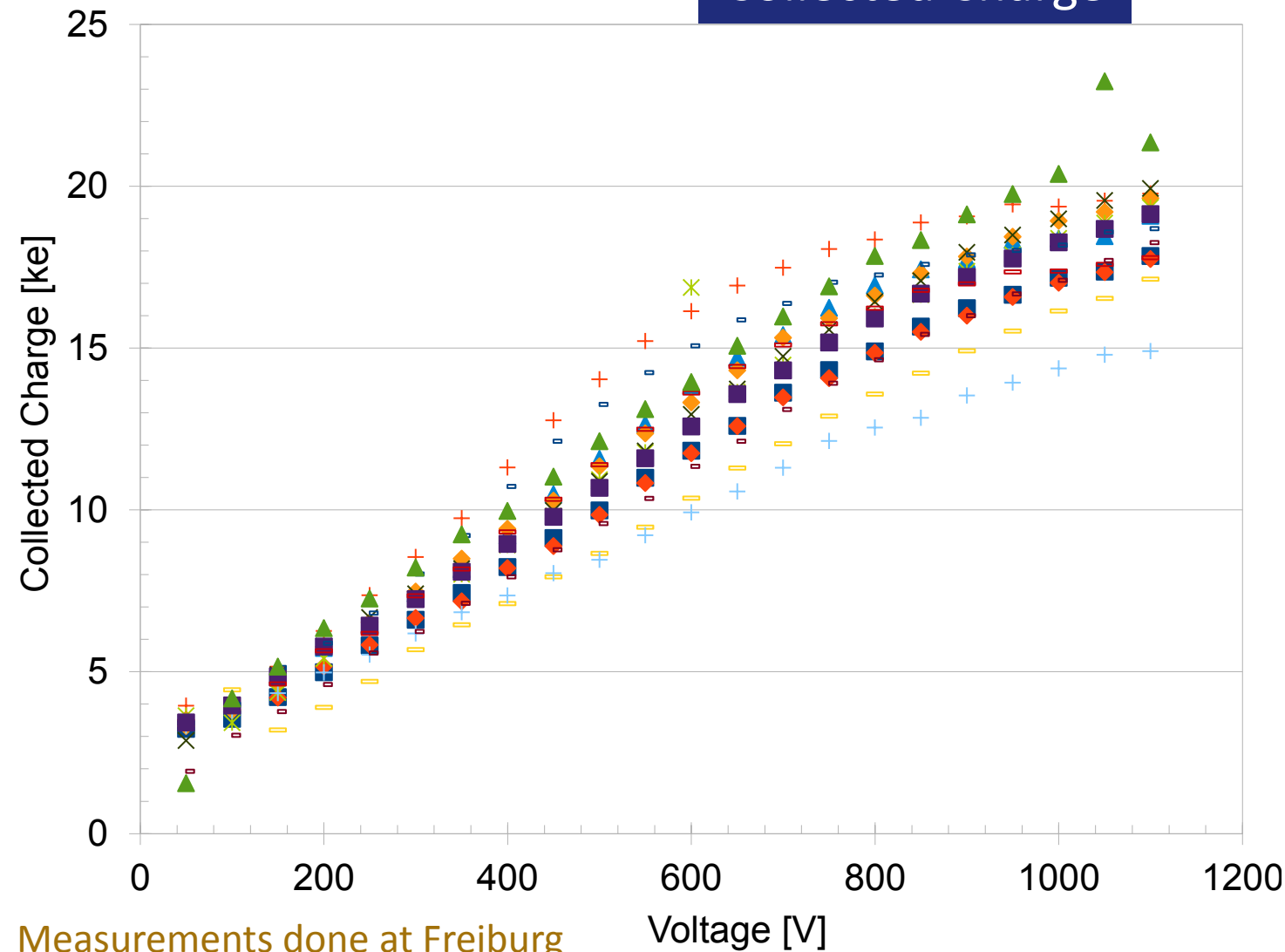
Comparability



- Compare results of same sensor geometry and type
- Freiburg and Liverpool show good agreement
=> Results are comparable between different sites



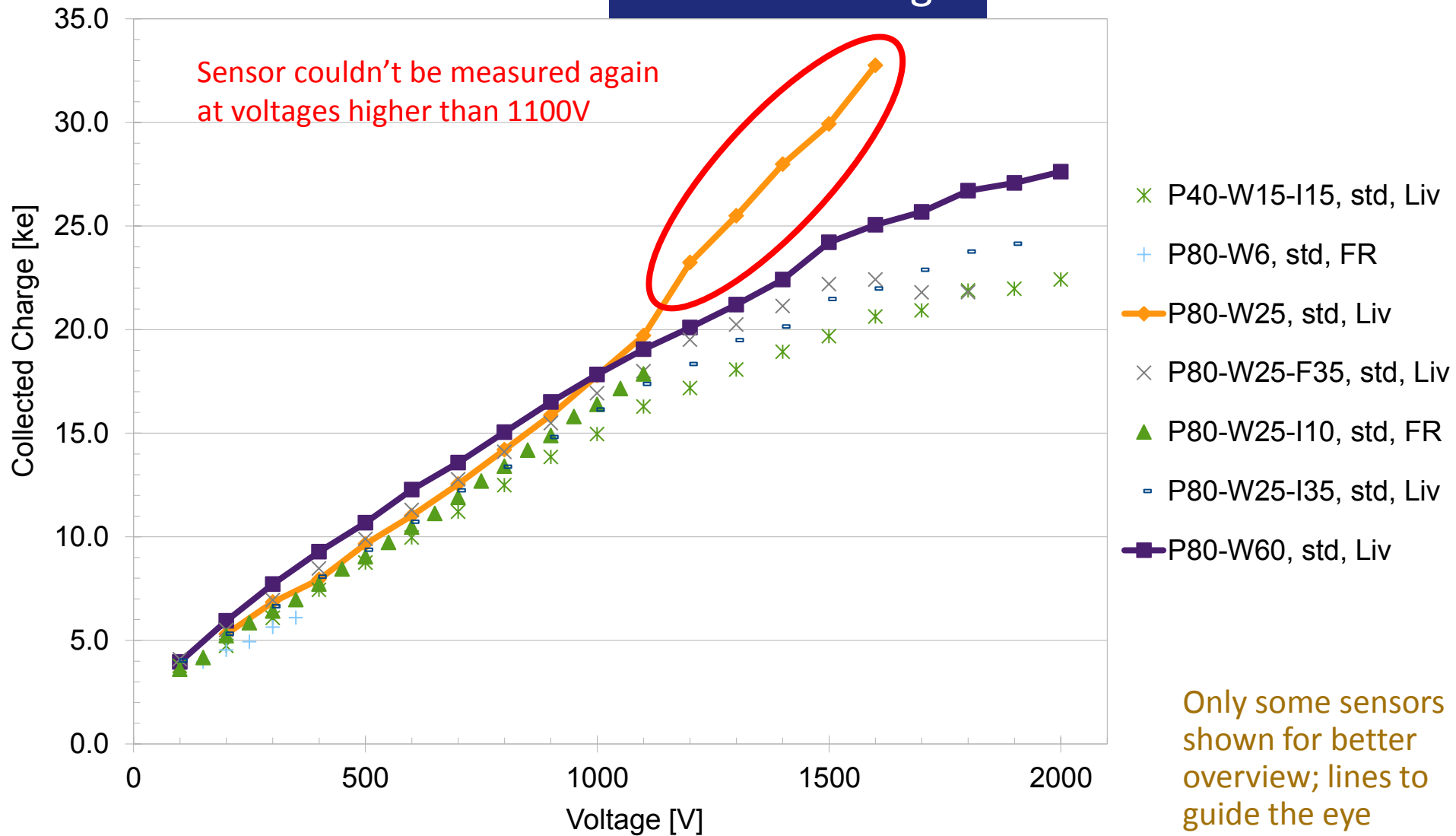
Collected Charge



- P40-W6, std
- P40-W15, std
- ◆ P40-W15-I6, std
- ▲ P80-W6, std
- ⊕ P80-W6, std
- ◇ P80-W25, std
- ✱ P80-W25-F10, std
- ✕ P80-W25-F35, std
- ⊕ P80-W25-I10, std
- P80-W25-I30, std
- ⊖ P100-W10, std
- P100-W10, std
- ⊖ P100-W33, std
- ▲ P100-W70, std

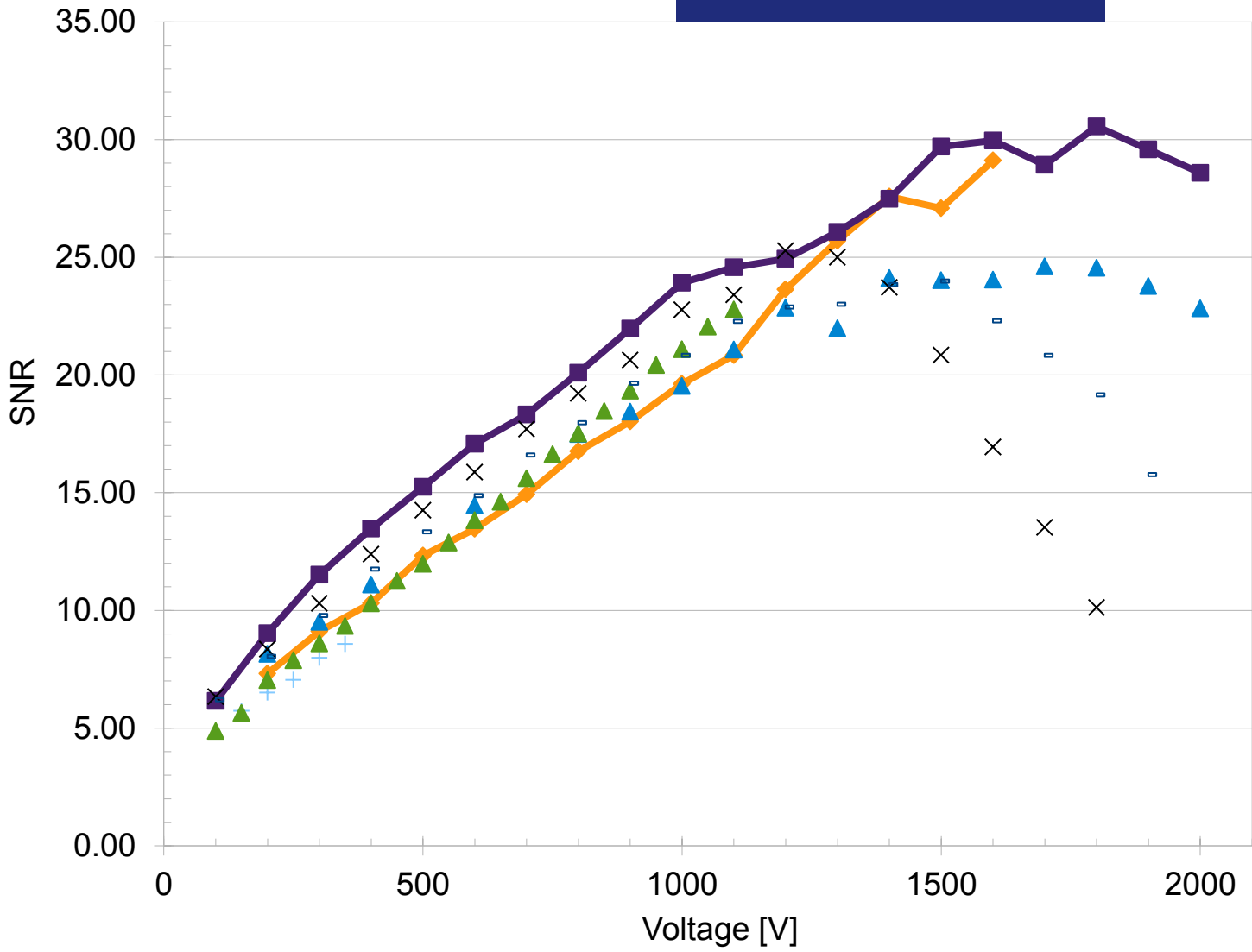


Collected Charge





SNR

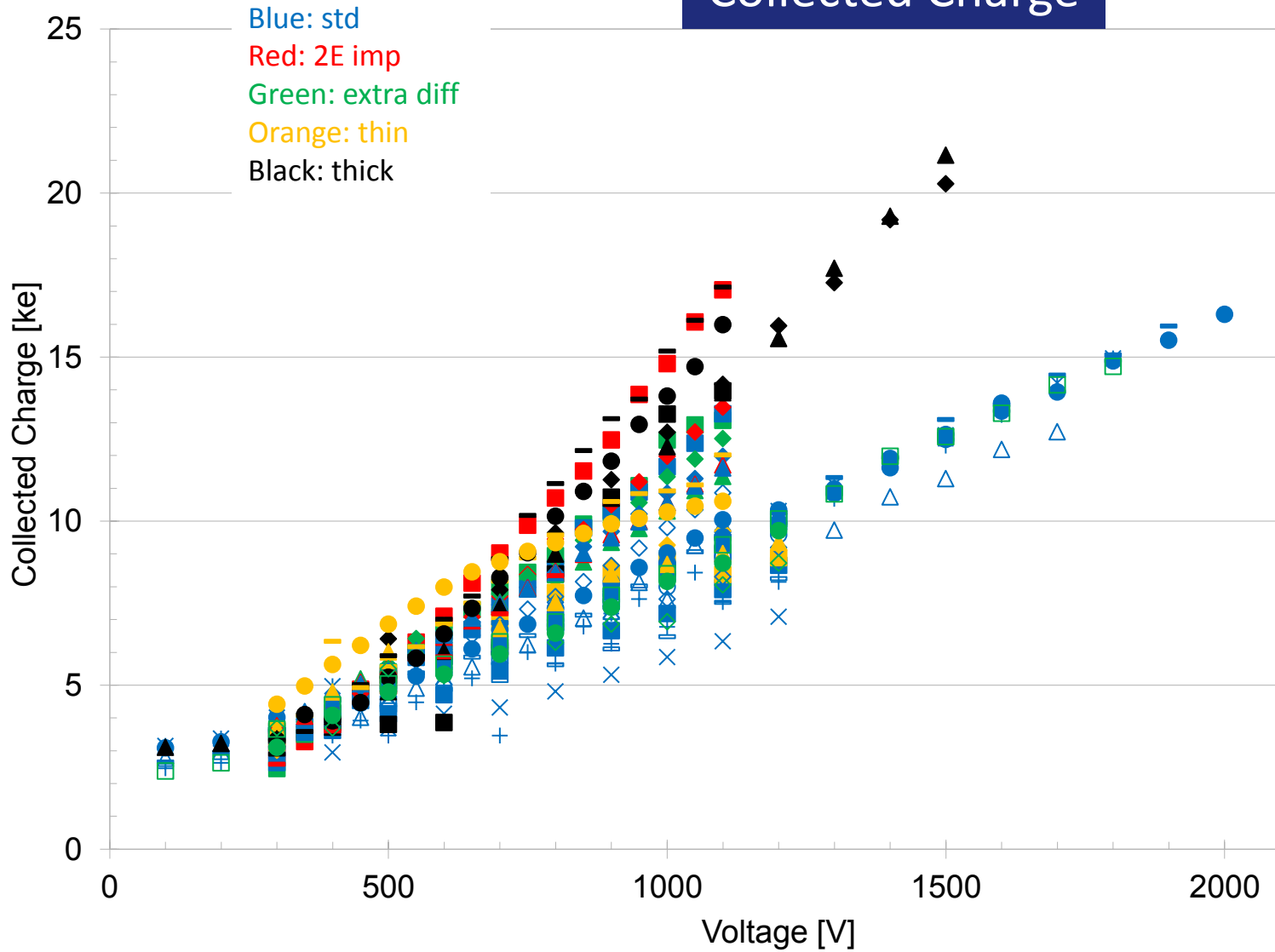


- ▲ P40-W15-I15, std, Liv
- + P80-W6, std, FR
- ◆ P80-W25, std, Liv
- × P80-W25-F35, std, Liv
- ▲ P80-W25-I10, std, FR
- P80-W25-I35, std, Liv
- P80-W60, std, Liv

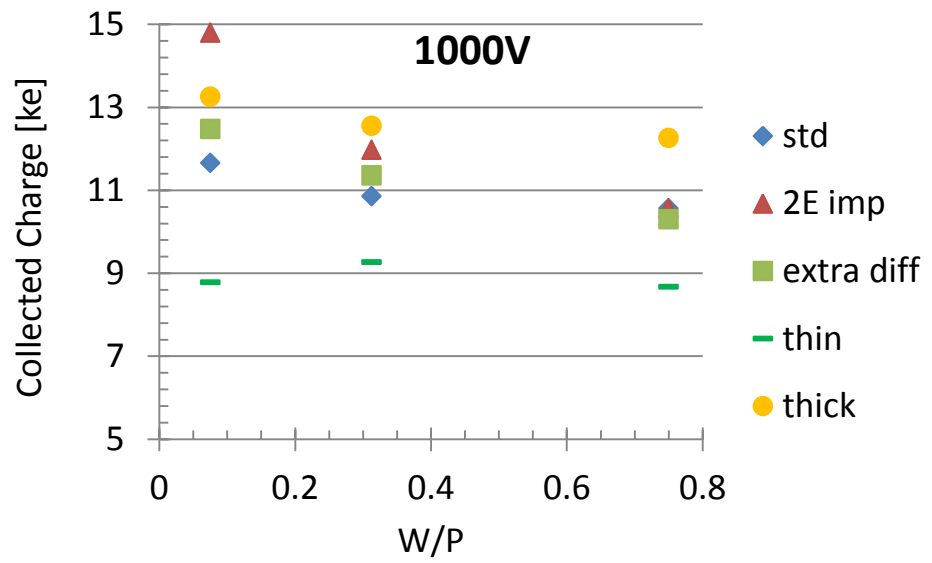
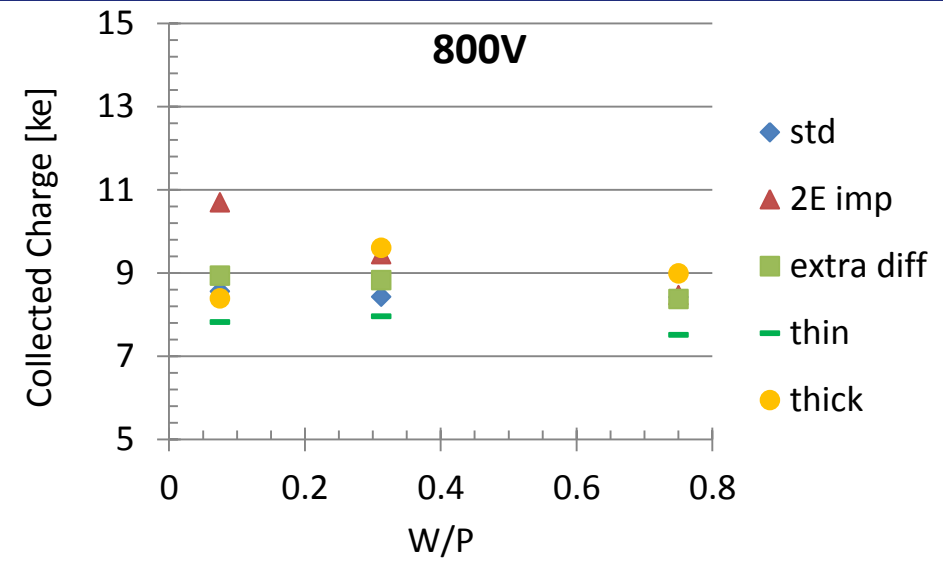
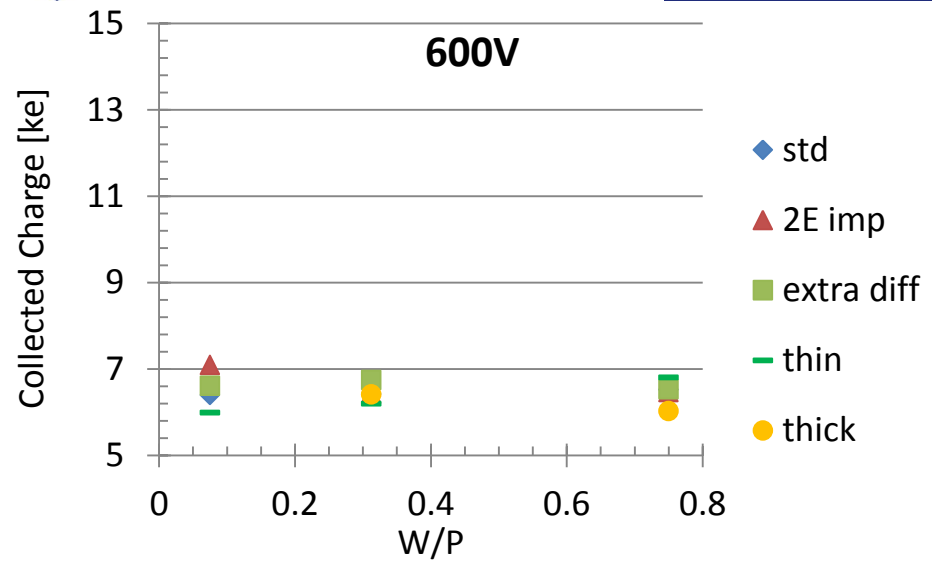
Only some sensors shown for better overview; lines to guide the eye



Collected Charge



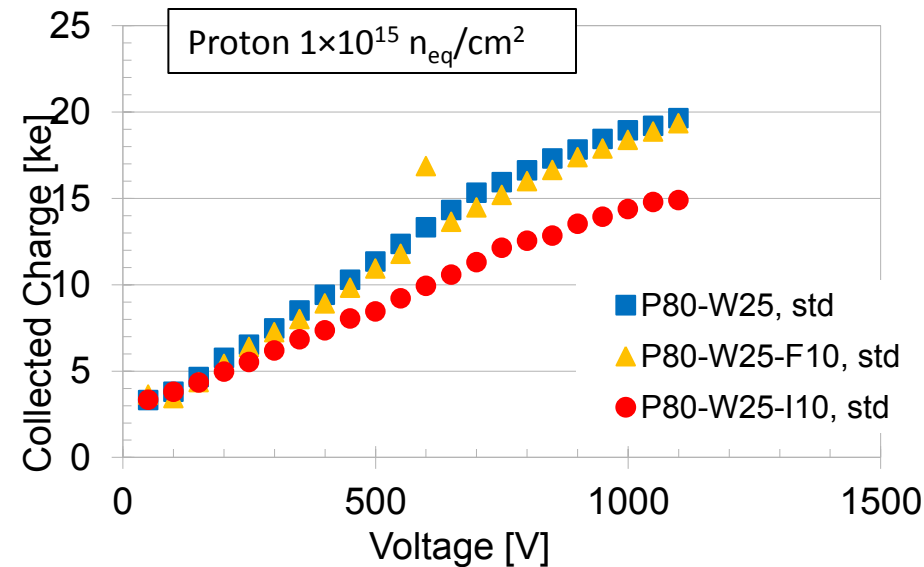
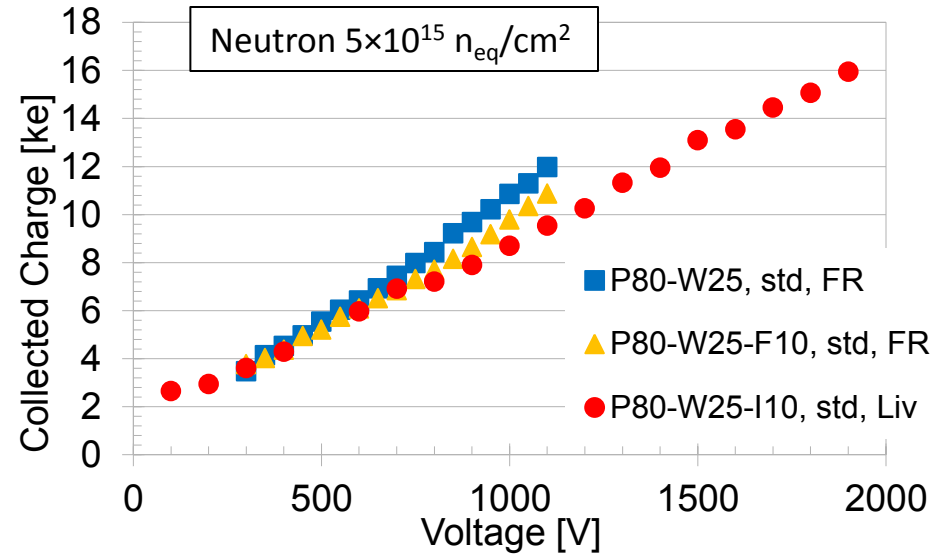
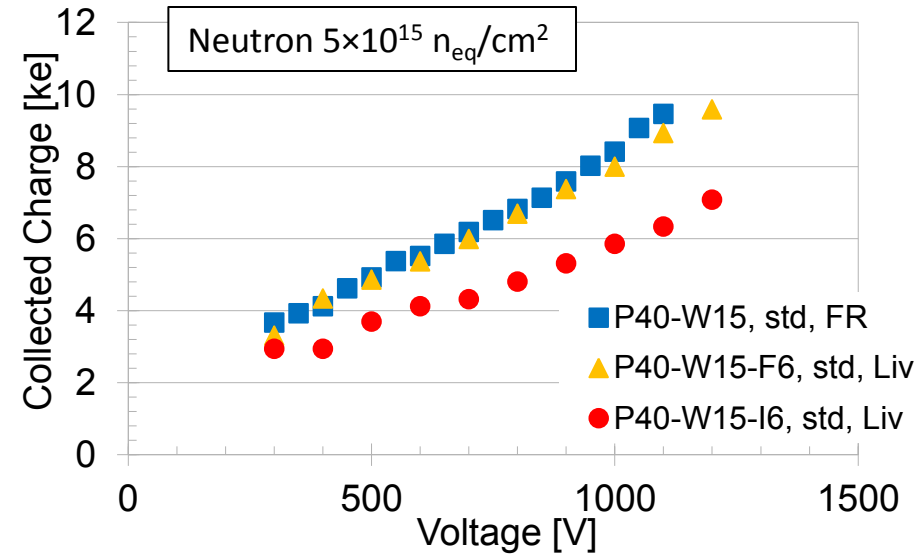
- △ P40-W6, std, FR
- △ P40-W6, std, Liv
- P40-W15, std, FR
- P40-W15, std, Liv
- P40-W15-F6, std, Liv
- × P40-W15-I6, std, Liv
- + P40-W15-I15, std, FR
- + P40-W15-I15, std, Liv
- + P40-W15-I15, std, Liv
- × P40-W27, std, Liv
- P80-W6, 2E imp, FR
- P80-W6, extra diff, FR
- P80-W6, std, FR
- P80-W6, std, Liv
- P80-W6, thin, Liv
- P80-W6, thick, Liv
- ◆ P80-W25, 2E imp, FR
- ◆ P80-W25, extra diff, FR
- ◆ P80-W25, std, FR
- ◆ P80-W25, thin, Liv
- ◆ P80-W25, thick, Liv, M2
- ◇ P80-W25-F10, std, FR
- ◇ P80-W25-F10, std, Liv
- P80-W25-I10, std, Liv
- P80-W25-I35, std, FR
- P80-W25-I35, std, Liv
- P80-W25-I35, std, Liv
- P80-W50, std, Liv
- ▲ P80-W60, extra diff, FR
- ▲ P80-W60, 2E imp, FR
- ▲ P80-W60, std, FR
- ▲ P80-W60, thin, Liv
- ▲ P80-W60, thick, Liv
- P100-W10, thick, FR
- P100-W10, thin, FR
- P100-W10, 2E imp, Liv
- P100-W33, thick, FR
- P100-W33-F33, extra diff, Liv
- P100-W33-I15, extra diff, Liv
- ◇ P100-W33-I33, extra diff, Liv
- P100-W70, thin, FR



- Charge multiplication only observed at $V_{bias} > 600V$
- Extra diff, 2E imp and thick show charge multiplication with respect to standard wafer
- Lower W/P ratio leads to more pronounced multiplication (as expected since fields are larger at strip edges)



Strip Structure



Detectors with biased intermediate strips (I) show a clear deficit of charge compared to no intermediate strip detectors or floating intermediate strip (F) detectors

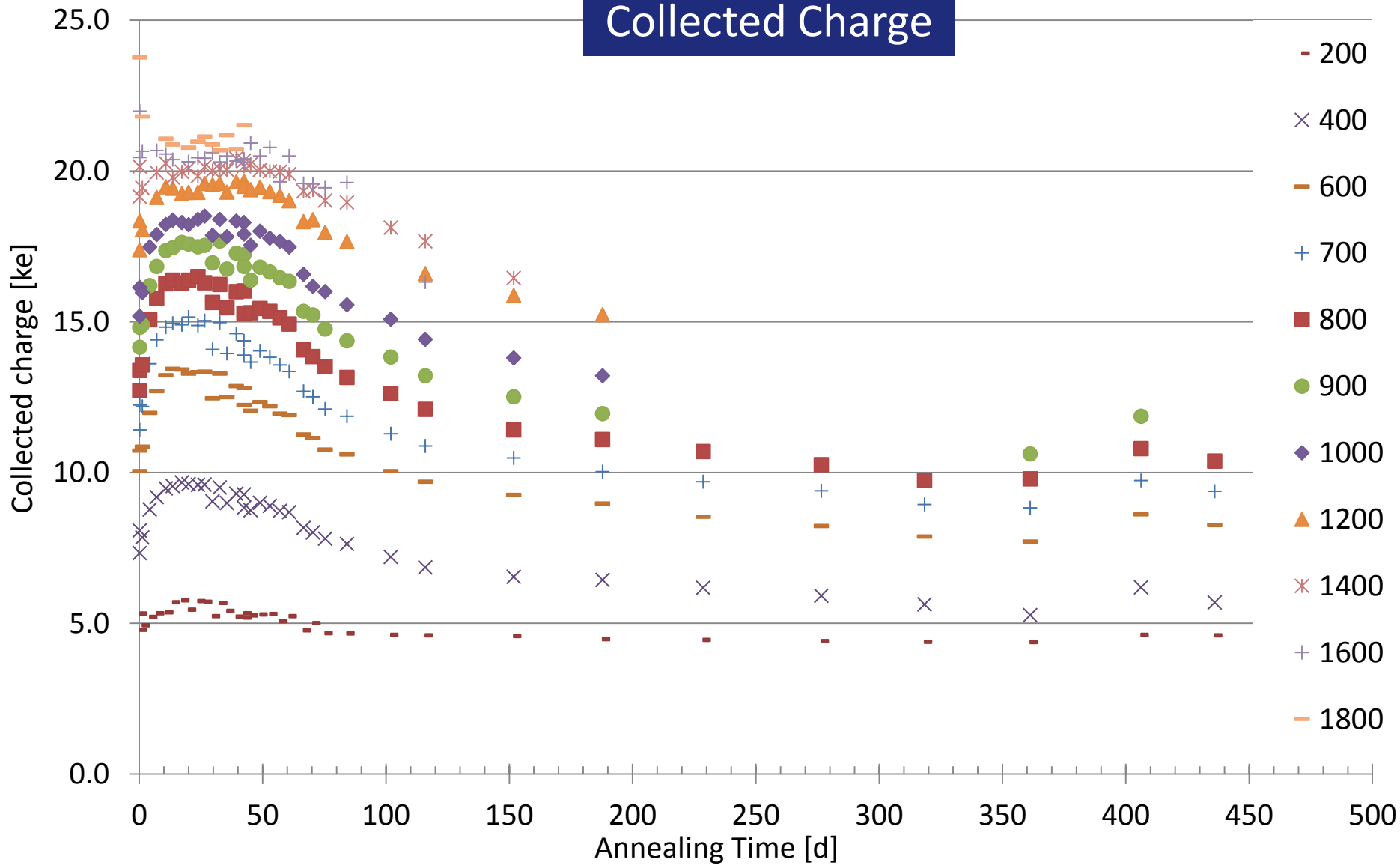


- Room temperature (20°C) annealing in nitrogen cabinet
- Sensors:
 - P80-W25-I35, std, Liv; $1 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$
 - P80-W25-I35, std, Liv; $5 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$



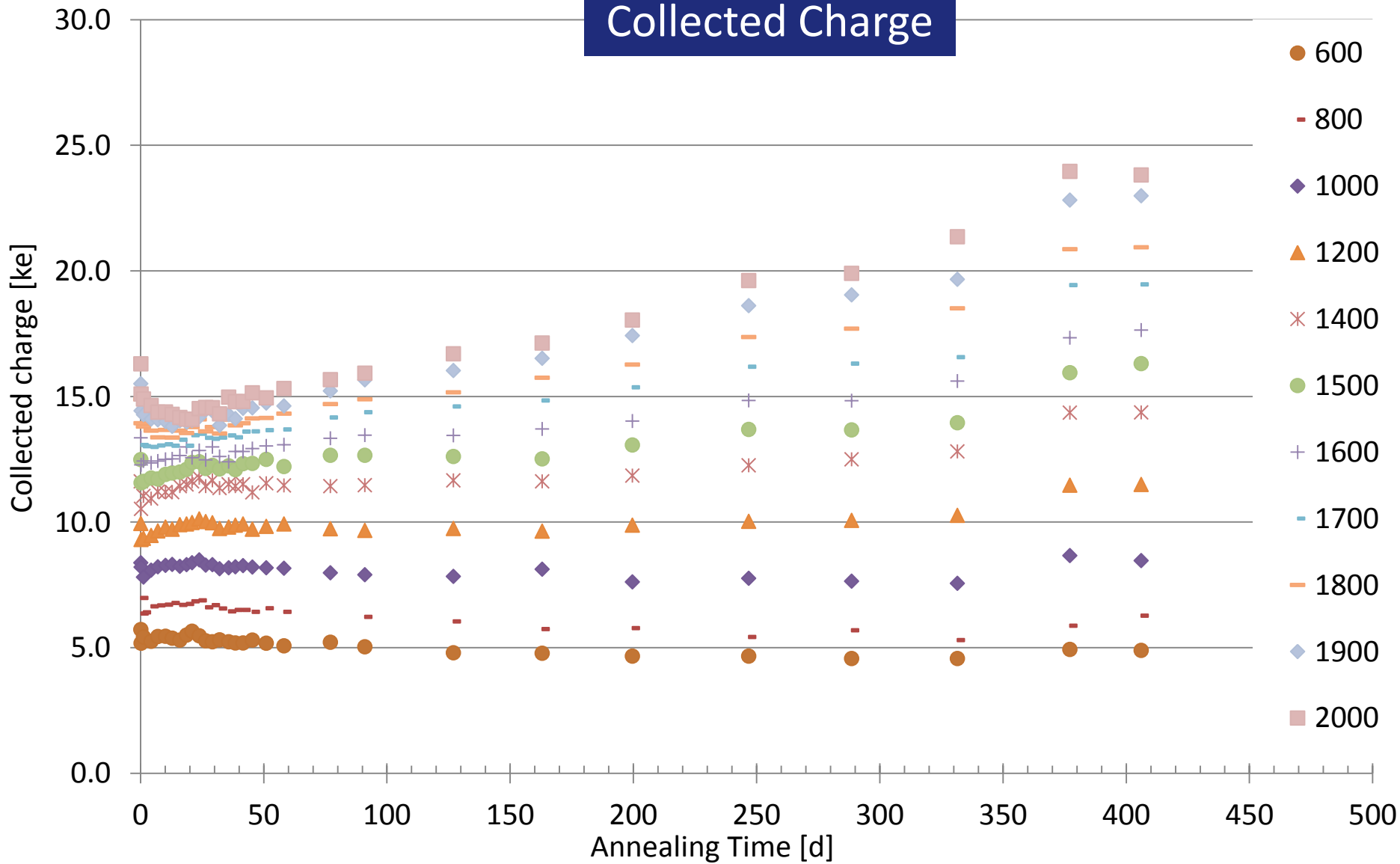


Collected Charge





Collected Charge



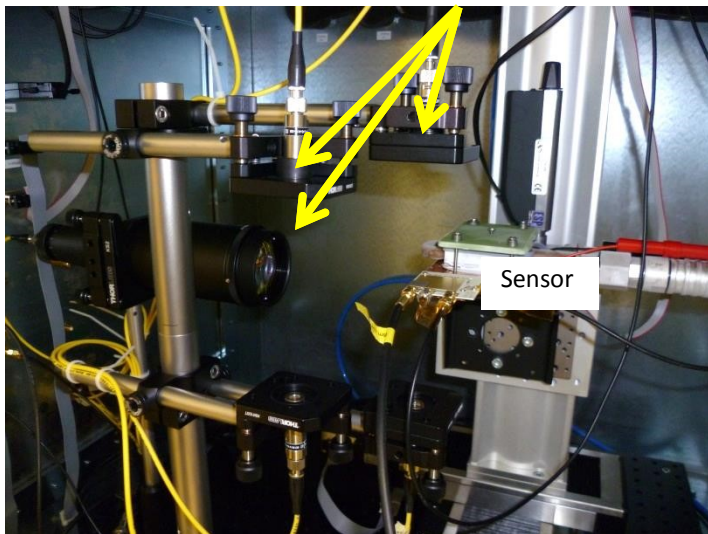


- **Transient Current Technique**
- Pulsed ps red/infrared laser illumination (front/edge) generates electron-hole pairs
 - Drift in electric field (external bias voltage)
 - Measure induced current in 5th strip
 - Amplified signal measured with digital oscilloscope
- Measurements performed at the CERN SSD laboratory
 - Two setups: TCT+ (TCT and eTCT), eTCT
 - Sensors cooled to -20°C
- ROOT based analysis software (CERN SSD group)



Setups

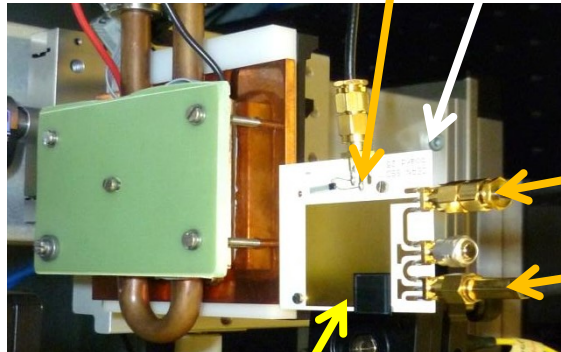
Laser



Cold block with chiller connection and peltier for cooling

PT1000 temperature sensor

PCB



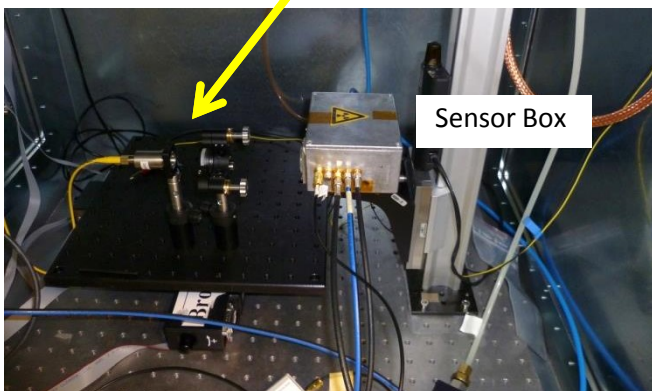
HV

5th strip readout

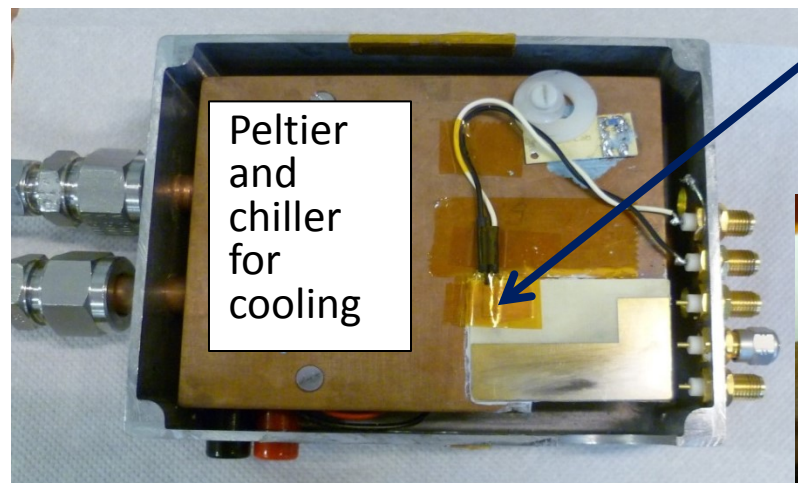
Silicon sensor

TCT+

Laser



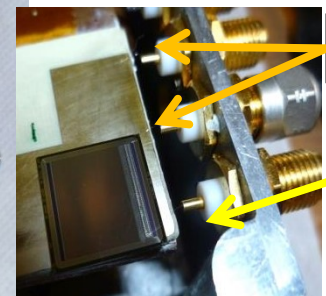
Sensor Box



Peltier and chiller for cooling

PT1000

eTCT

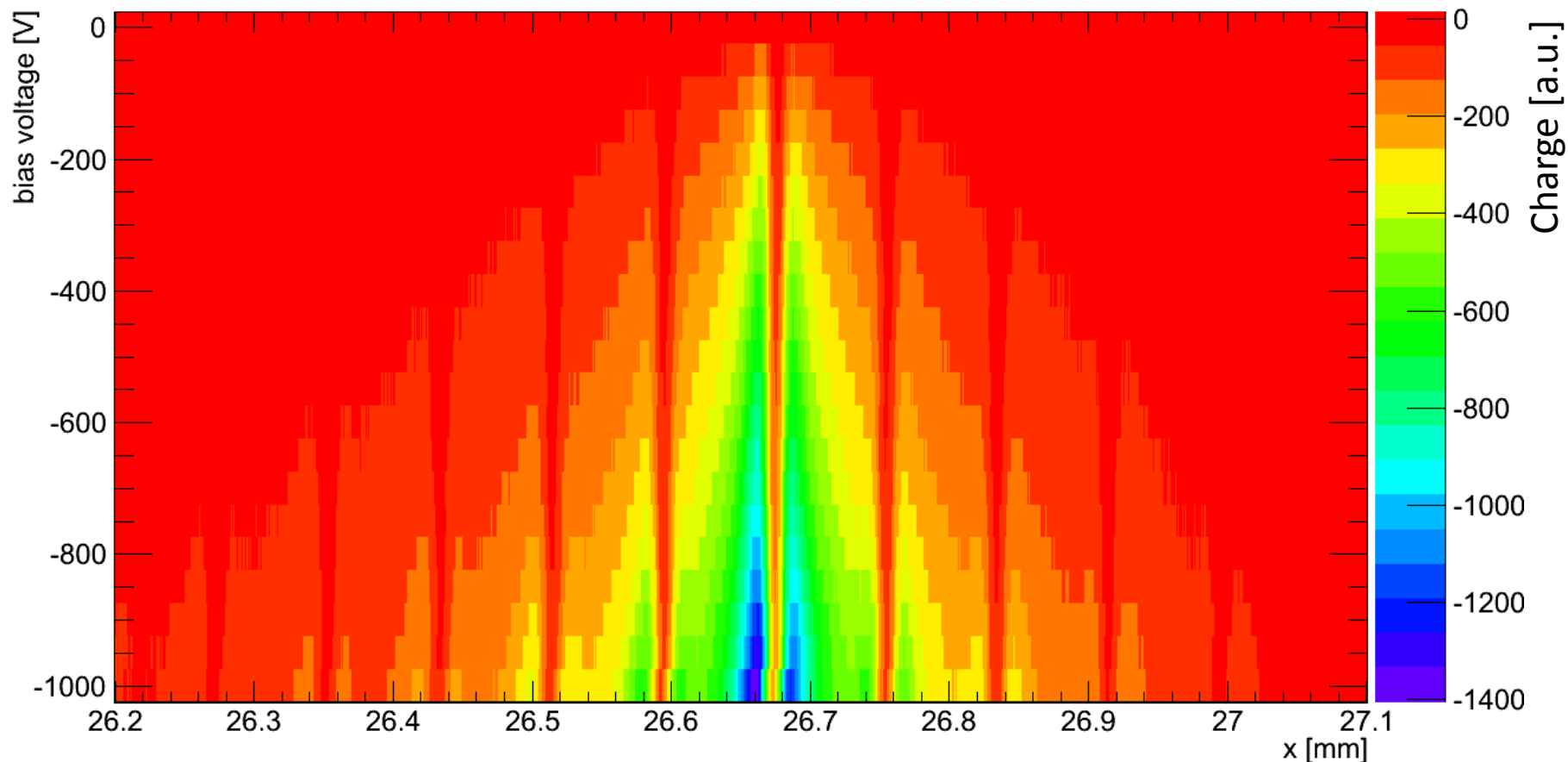


HV

5th strip



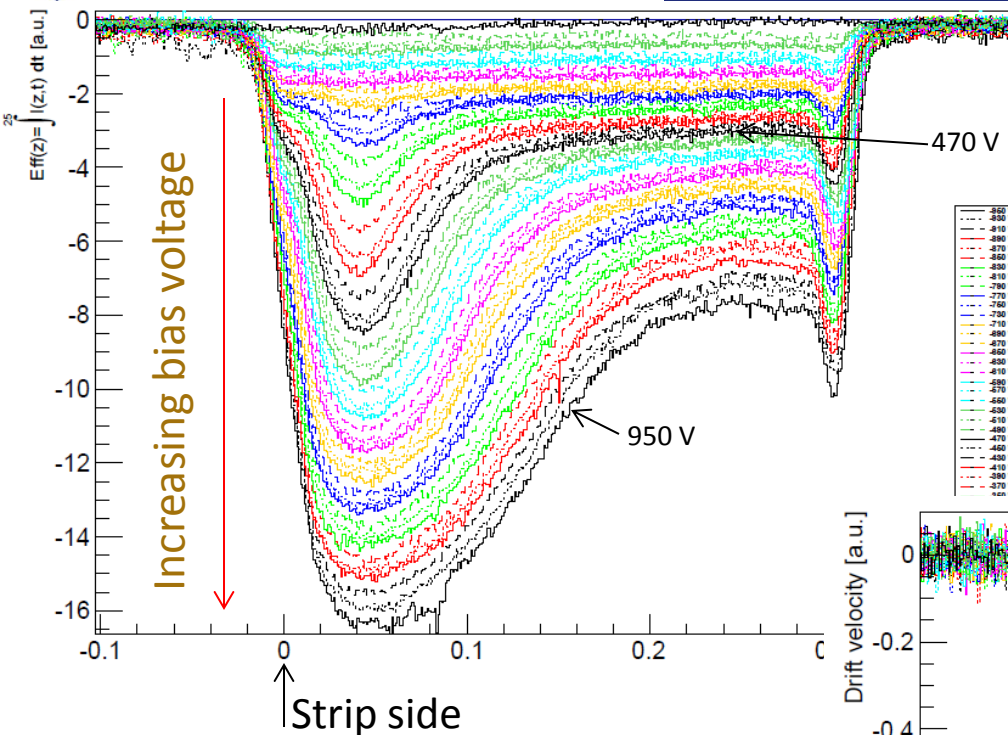
IR top



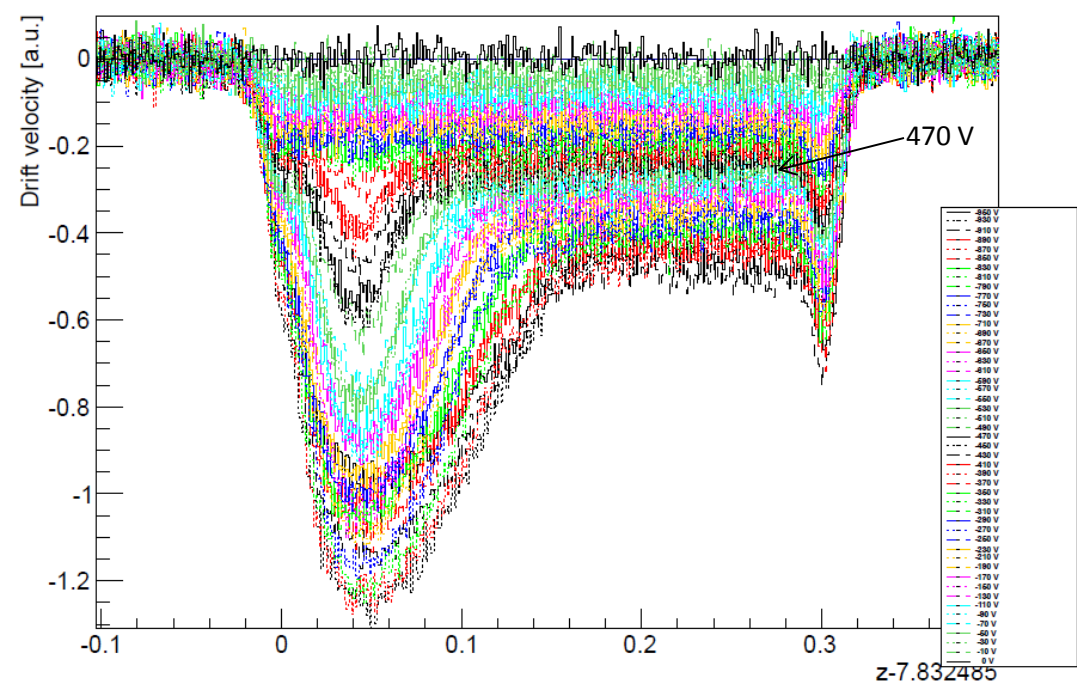
- With increasing bias voltage the collected charge at the 5th strip increase
- Sensitive distance from readout strip increase as well



edge



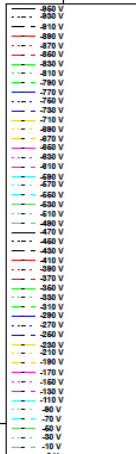
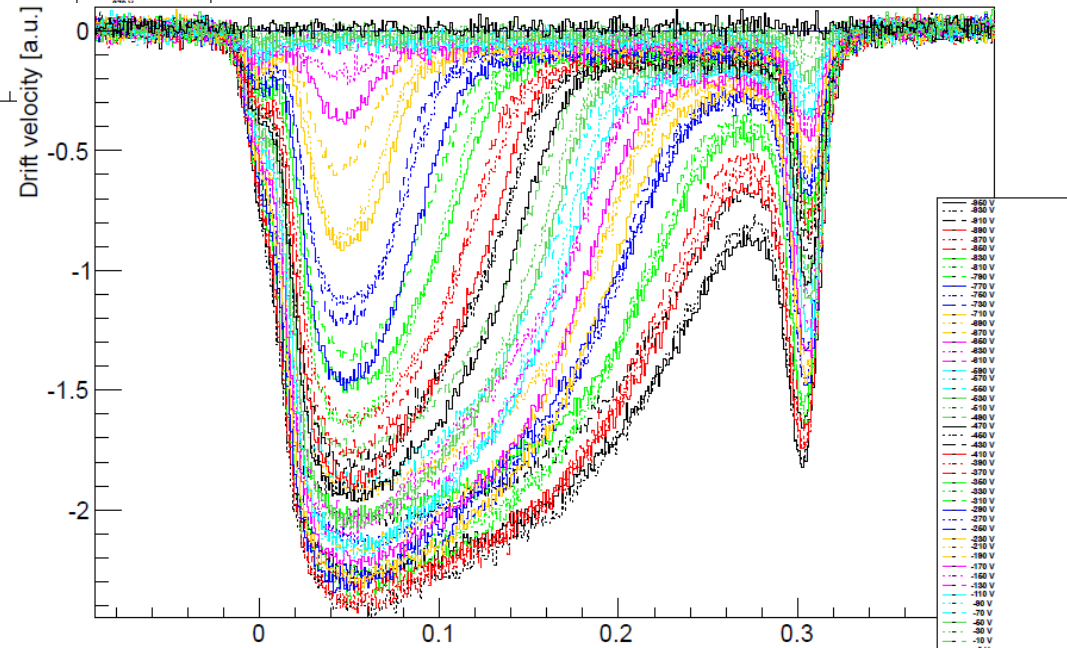
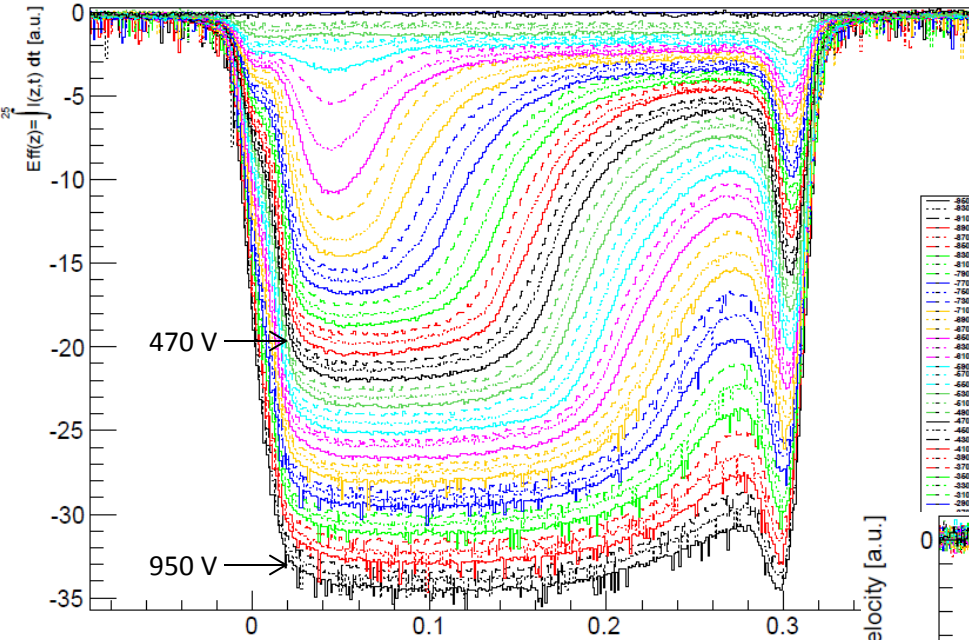
Efficiency correlated to charge, drift velocity correlated to electric field



- Highest efficiency at p-n junction
- With increasing bias voltage, high efficiency region “grows”
- Peak on backside most likely because of doping concentration difference between bulk (p) and backside contact (p+)



edge



- Sensor almost complete depleted at 950V

z-7.84135Z



- No charge multiplication observed in unirradiated sensors
- No sign of charge multiplication after proton irradiation with $1 \times 10^{15} n_{eq}/cm^2$; measured noise is nearly constant in full voltage range
- Neutron Irradiation with $1 \times 10^{15} n_{eq}/cm^2$
 - P80-W25 and P80-W60 (both std) show signs of charge multiplication
- Neutron Irradiation with $5 \times 10^{15} n_{eq}/cm^2$
 - Three wafer types (2E imp, extra diff, thick) show signs of charge multiplication for voltages higher than 600V with no decrease in the signal-to-noise ratio
 - Enhancement of charge is small, but consistent among wafer types relative to std for various sensor geometries
 - Low Width/Pitch ratio leads to more multiplication, as expected since fields are larger at strip edge
- Detectors with intermediate strips show less collected charge than sensors without
 - Detectors with floating intermediate strips show only a small deficit
 - Detectors with biased intermediate strips show clearly a charge deficit
- Annealing:
 - The collected charge of P80-W25-I35 (std), irradiated to $1 \times 10^{15} n_{eq}/cm^2$, increase in the first few days and then decrease
 - For P80-W25-I35 (std), irradiated to $5 \times 10^{15} n_{eq}/cm^2$, the collected charge is increasing with annealing time for voltages above 1200V, which is caused by charge multiplication
- TCT/eTCT
 - First measurements of sensors performed
 - Increase of depleted region with increasing bias voltage clearly visible
 - Measurements of further sensors will follow



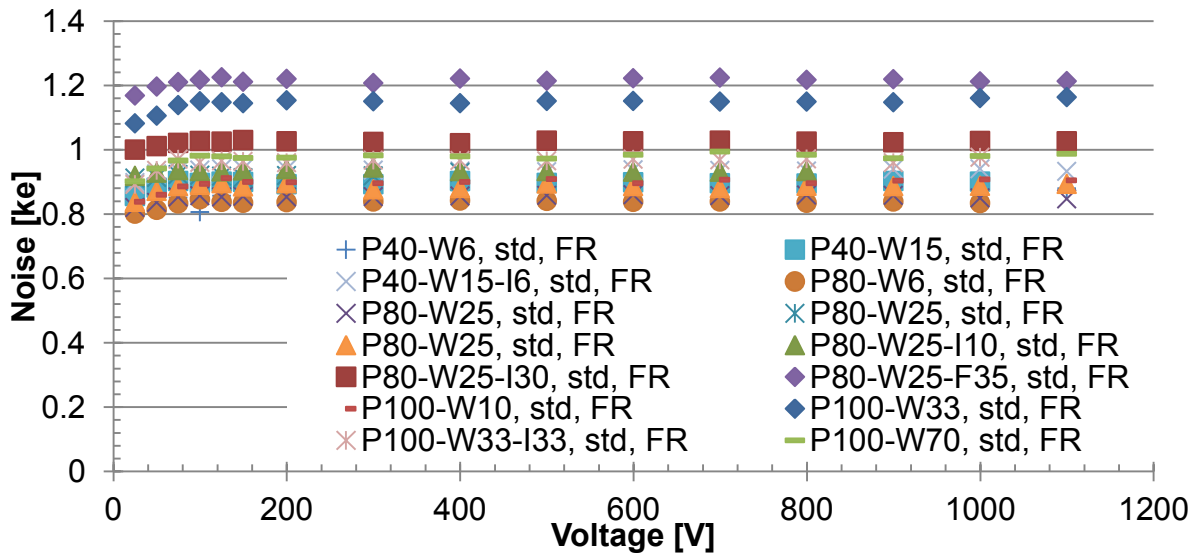
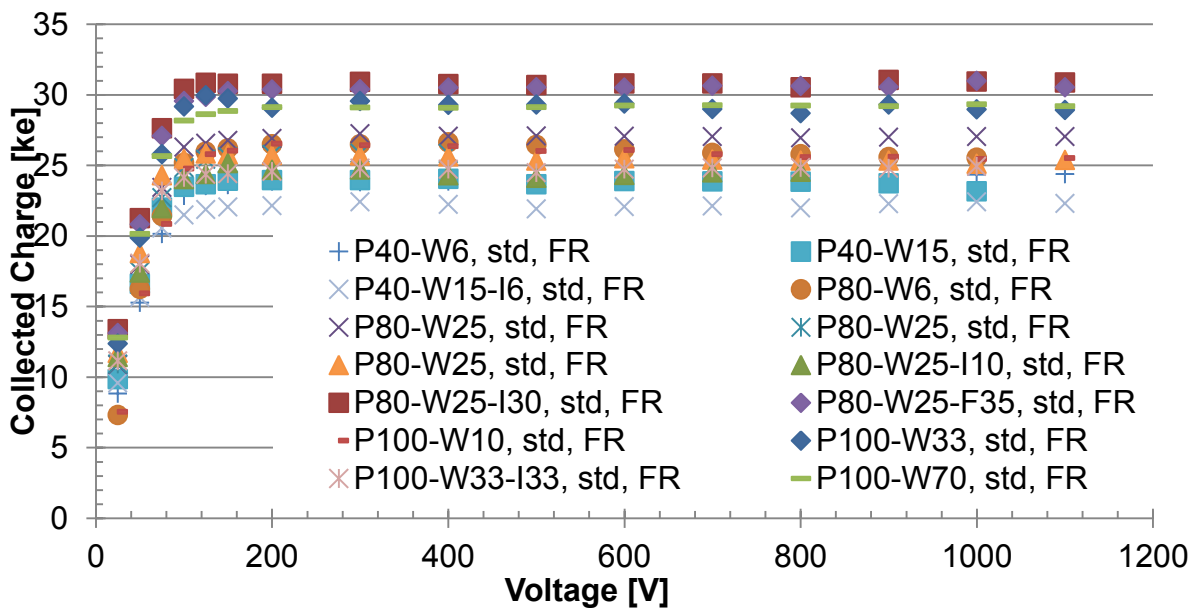
- Irradiations supported by the Initiative and Networking Fund of the Helmholtz Association, contract HA-101 (“Physics at the Terascale”)
- The research leading to these results has received funding from the European Commission under the FP7 Research Infrastructures project AIDA, grant agreement no. 262025
- We would like to thank the irradiation teams at Ljubljana and Karlsruhe
- We would like to thank Christian, Marcos , Hannes and Michael at CERN for the help wit the TCT measurements and sharing their setups.



BACKUP



Unirradiated Results

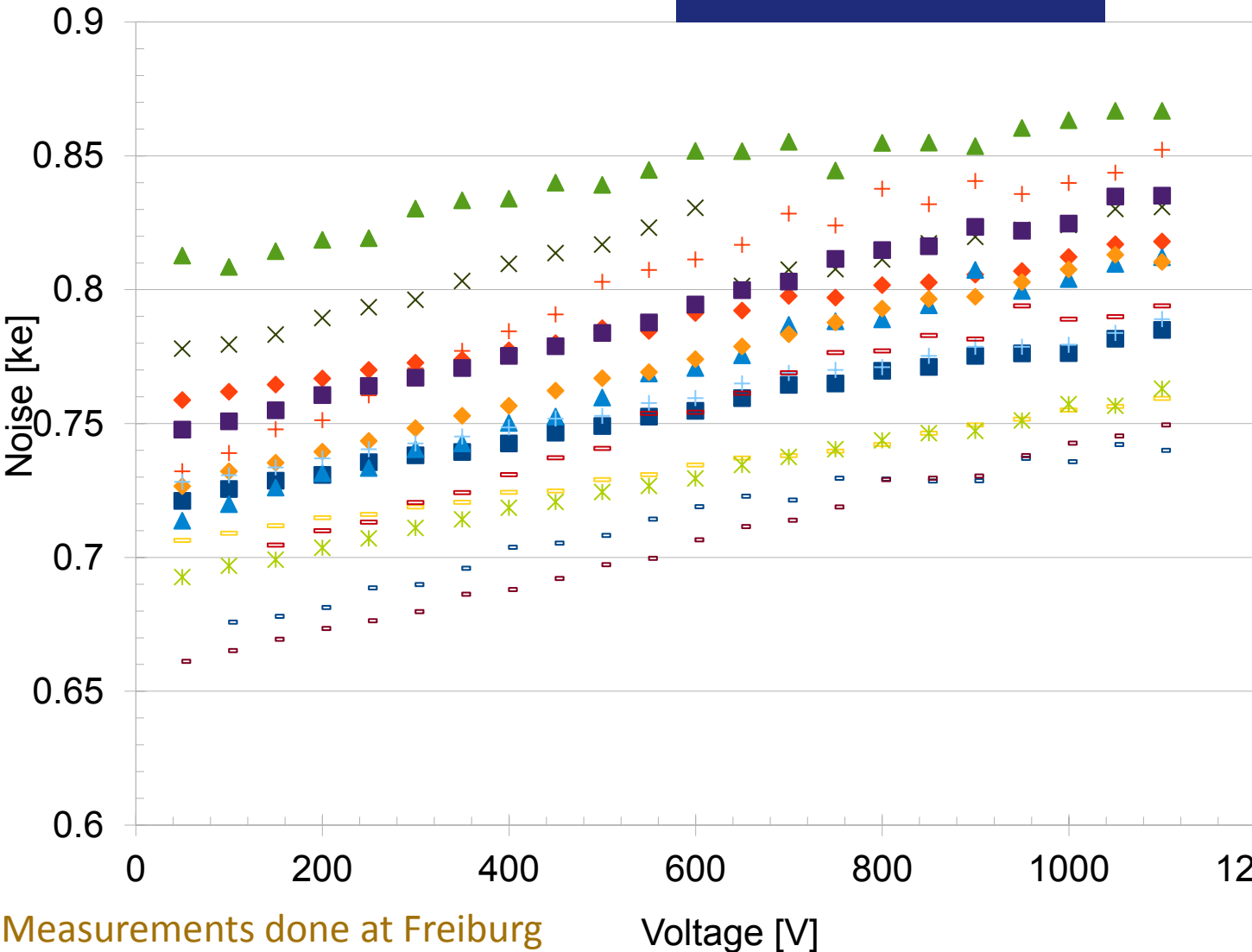


- Full depletion reached at 100-125V
- No charge multiplication observed up to 1100V
- Most sensors show no breakdown up to 1100V
- Large spread of collected charge -> see C. Betancourt, 21st RD50 Workshop

Measurements done at Freiburg



Noise

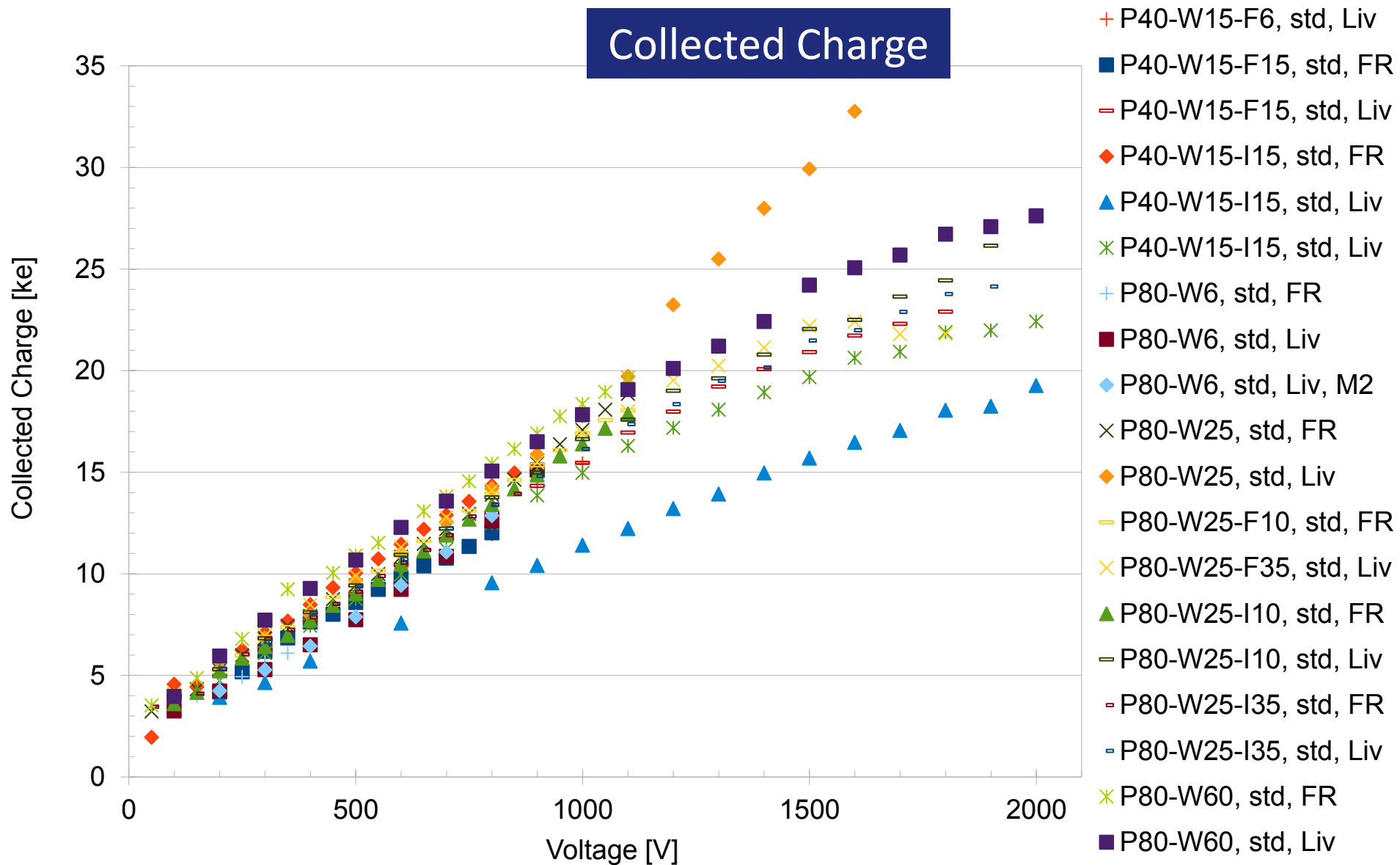


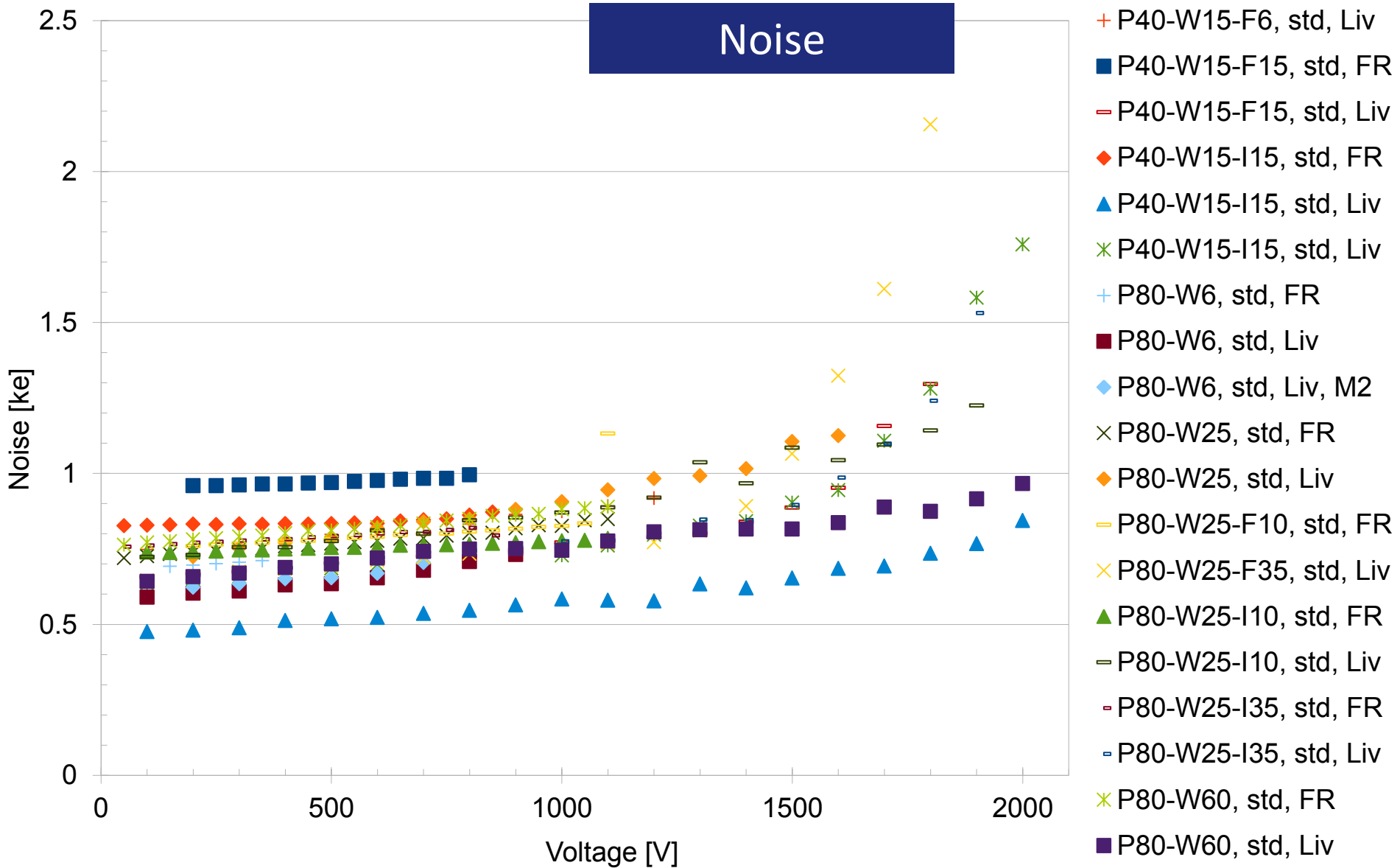
- P40-W6, std
- P40-W15, std
- ◆ P40-W15-I6, std
- ▲ P80-W6, std
- + P80-W6, std
- ◇ P80-W25, std
- * P80-W25-F10, std
- × P80-W25-F35, std
- + P80-W25-I10, std
- P80-W25-I30, std
- P100-W10, std
- P100-W10, std
- P100-W33, std
- ▲ P100-W70, std

Measurements done at Freiburg



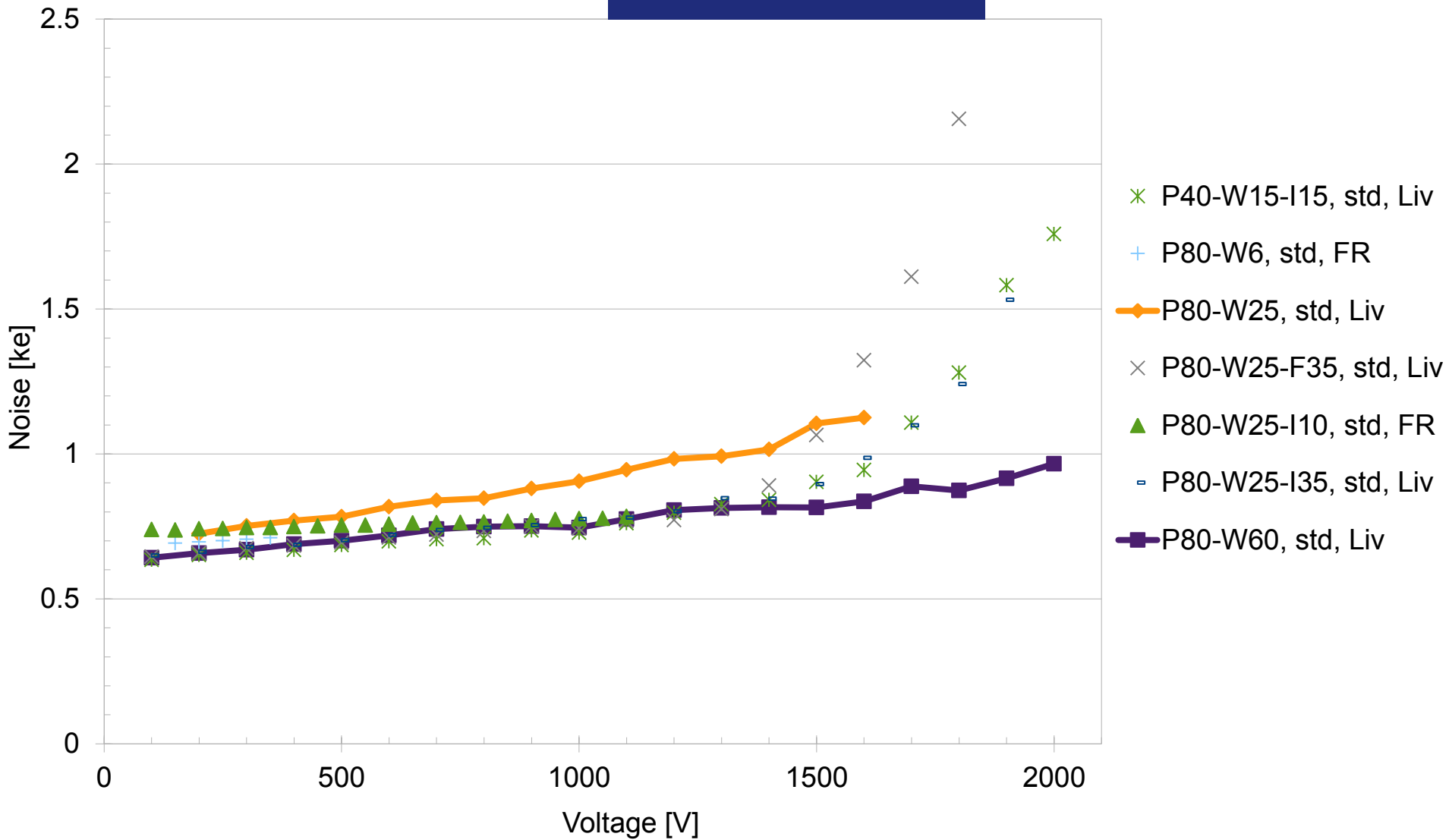
Collected Charge

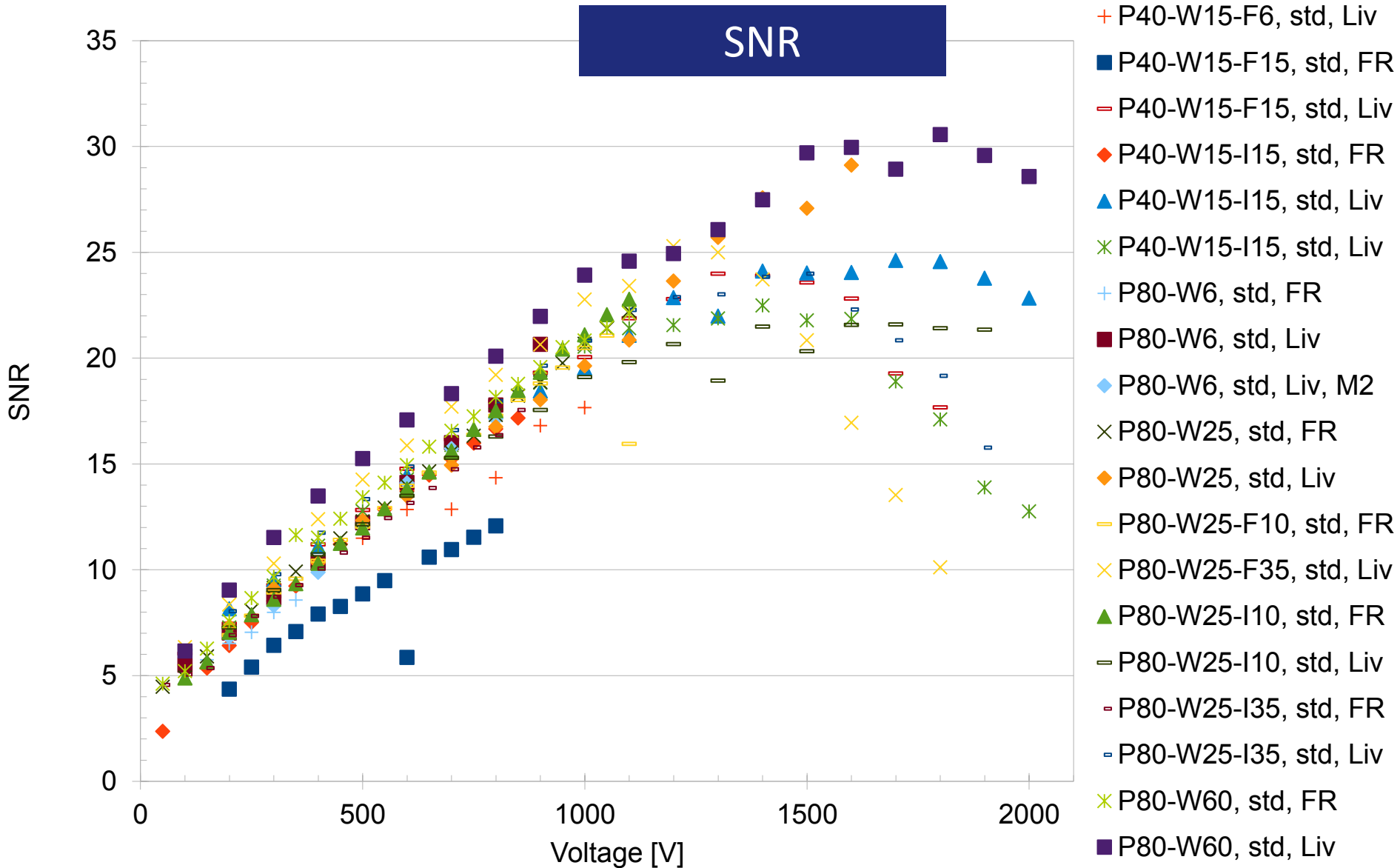






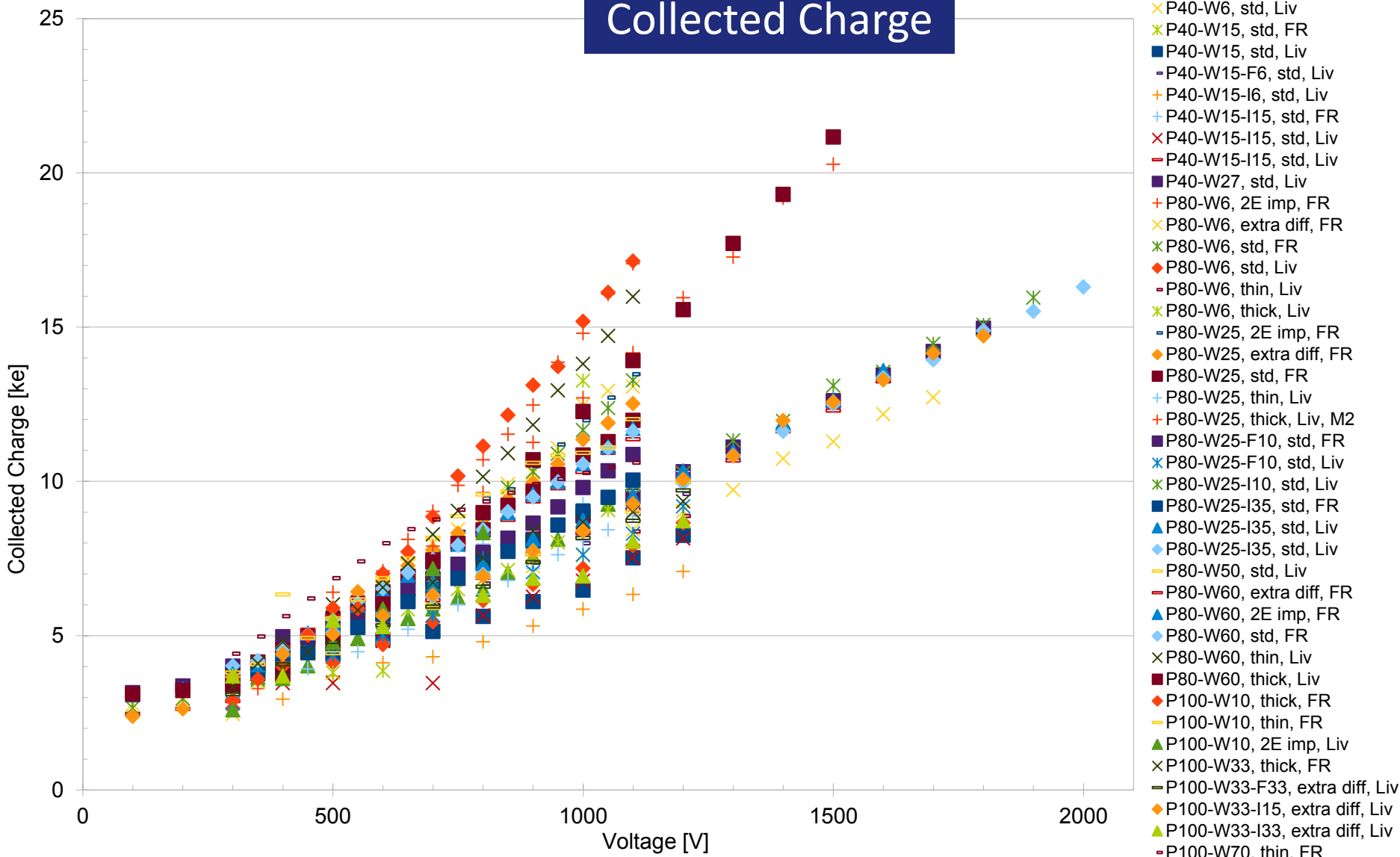
Noise

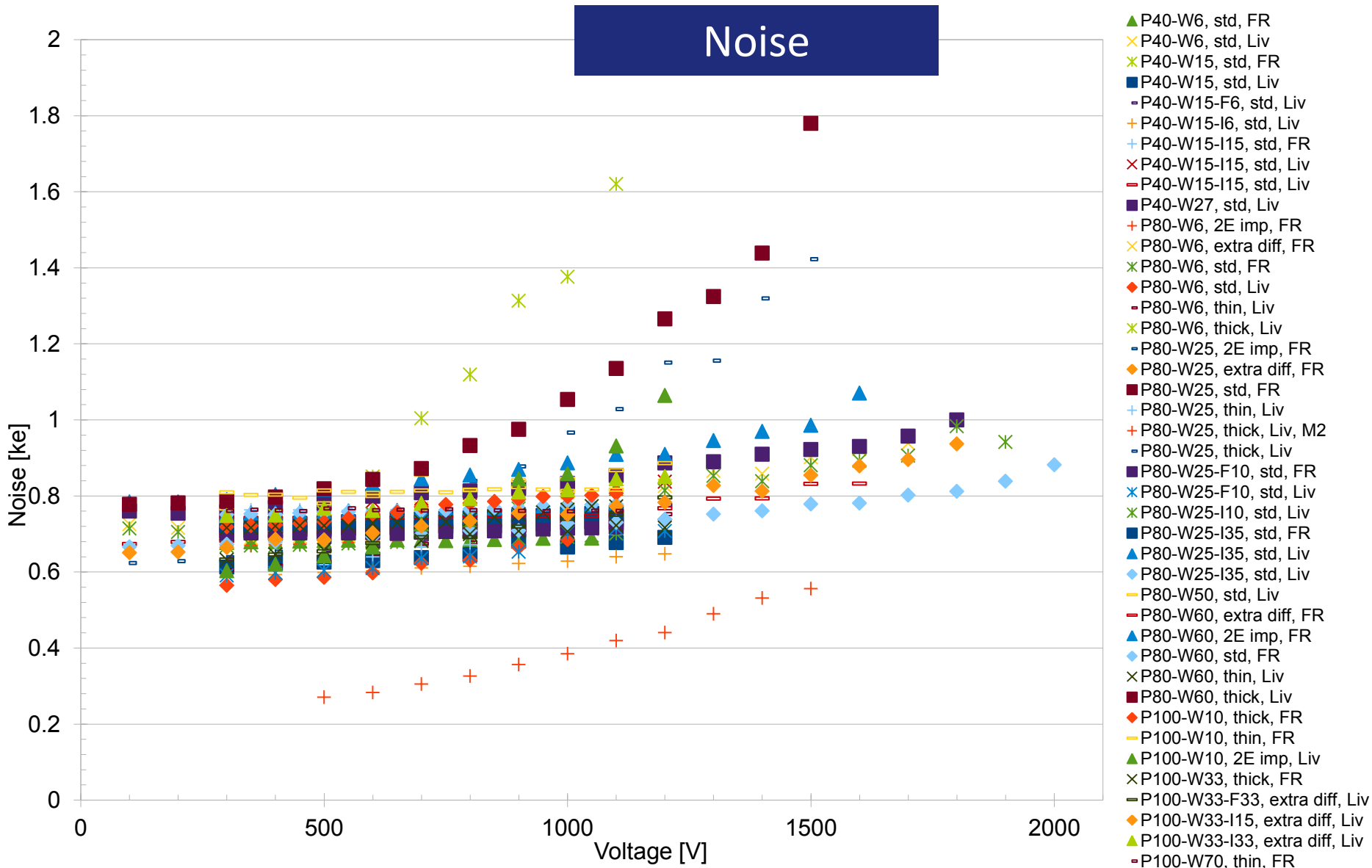


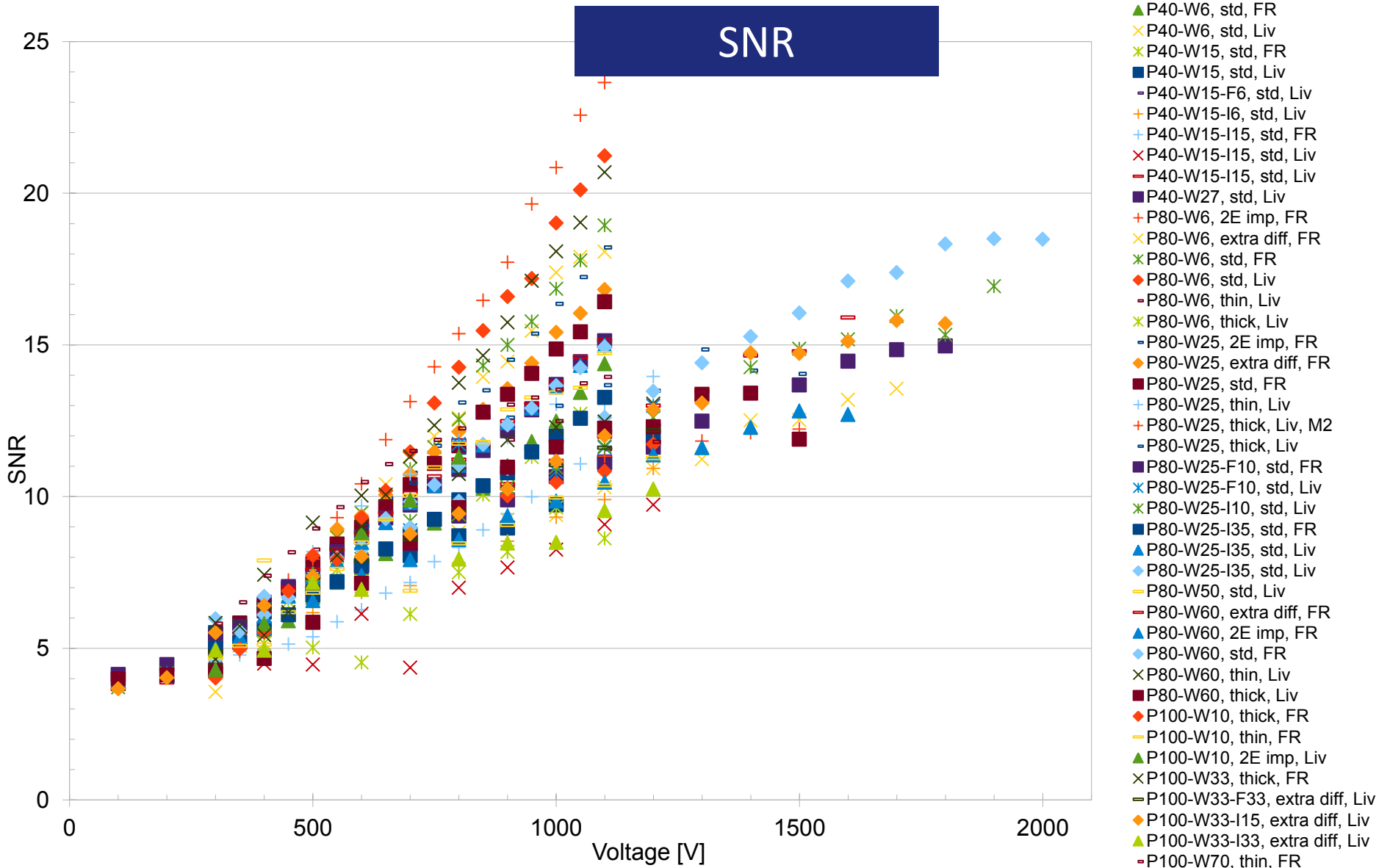


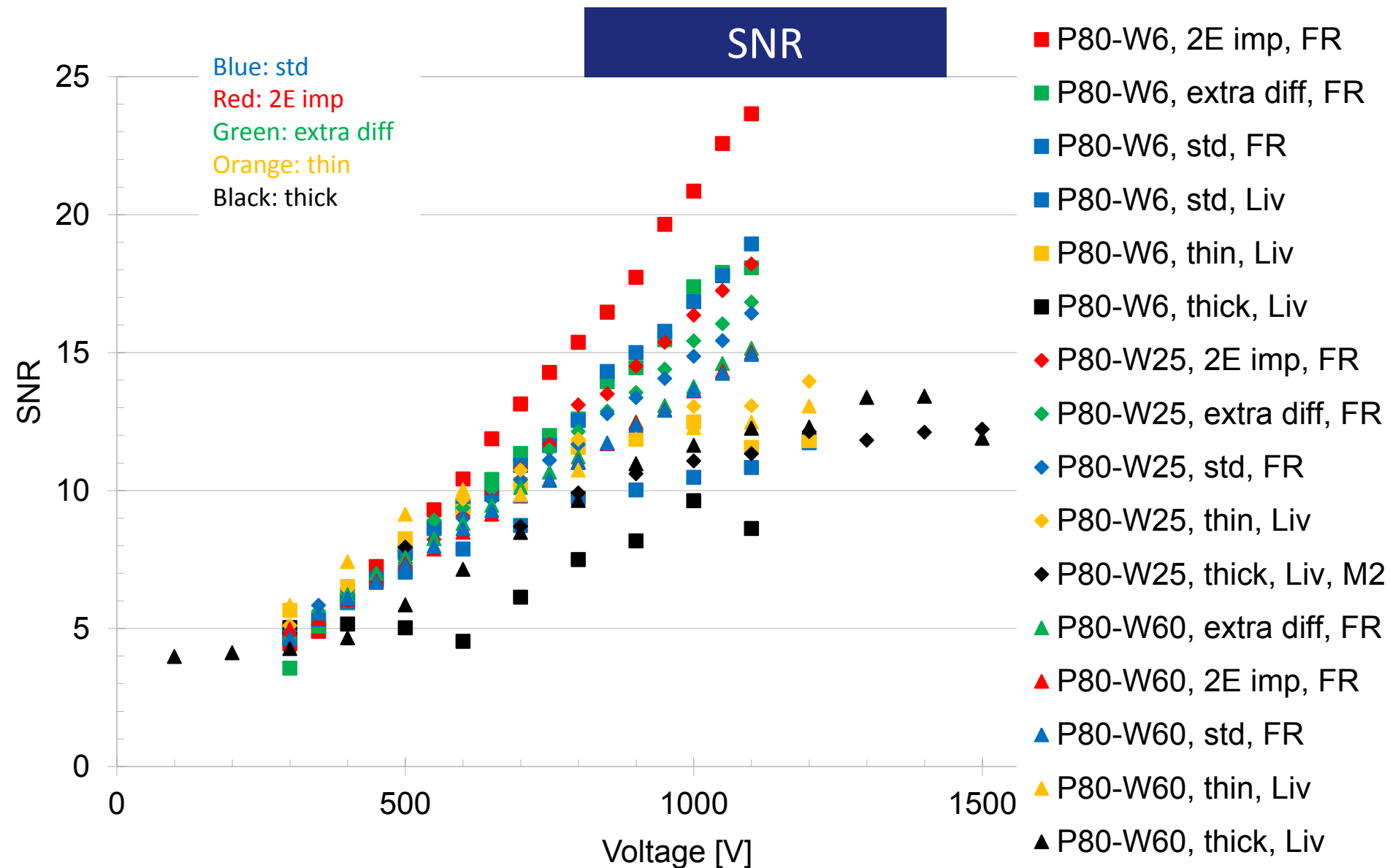


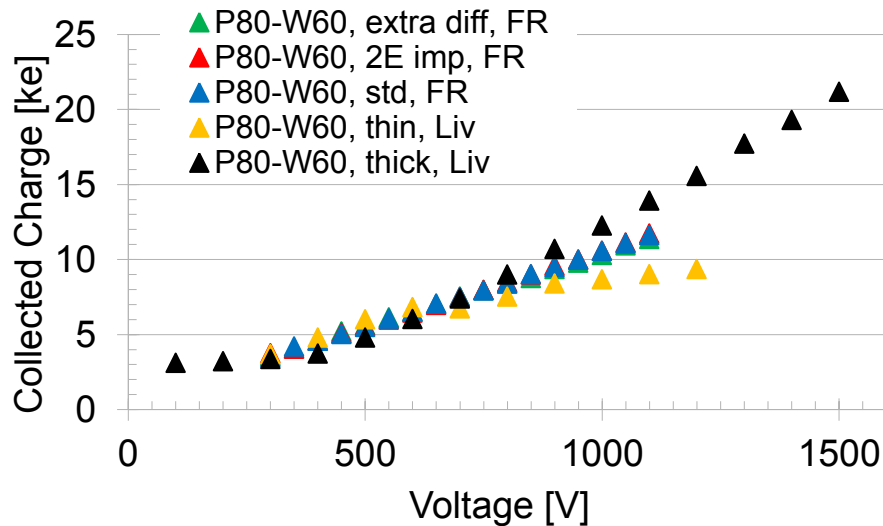
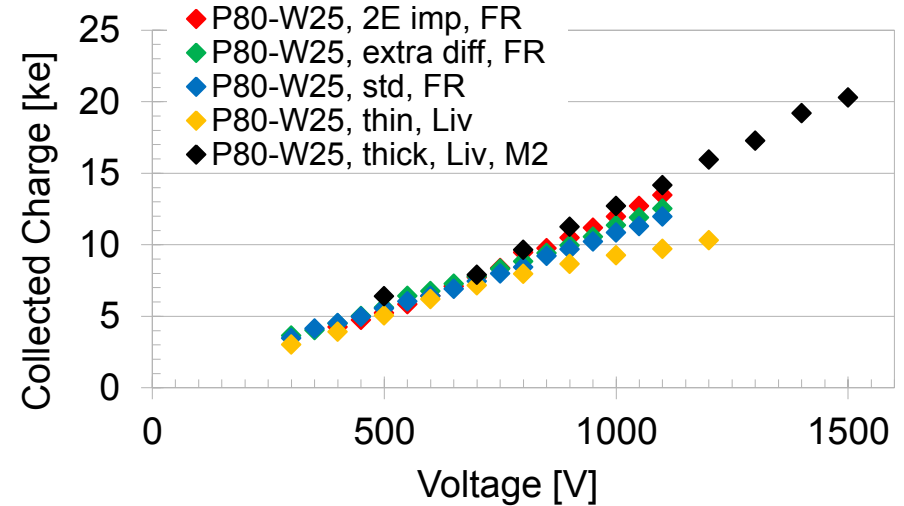
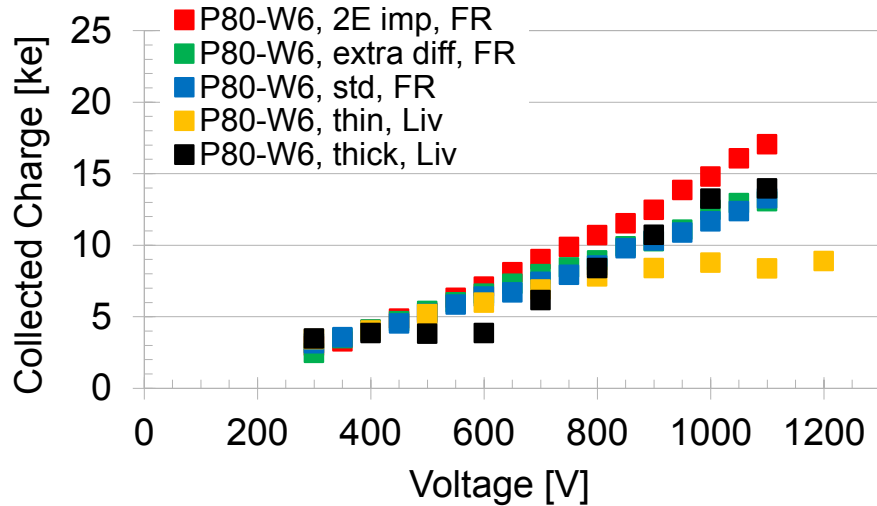
Collected Charge











Double implant energy
(2E imp) and thick
sensors show in general
more collected charge